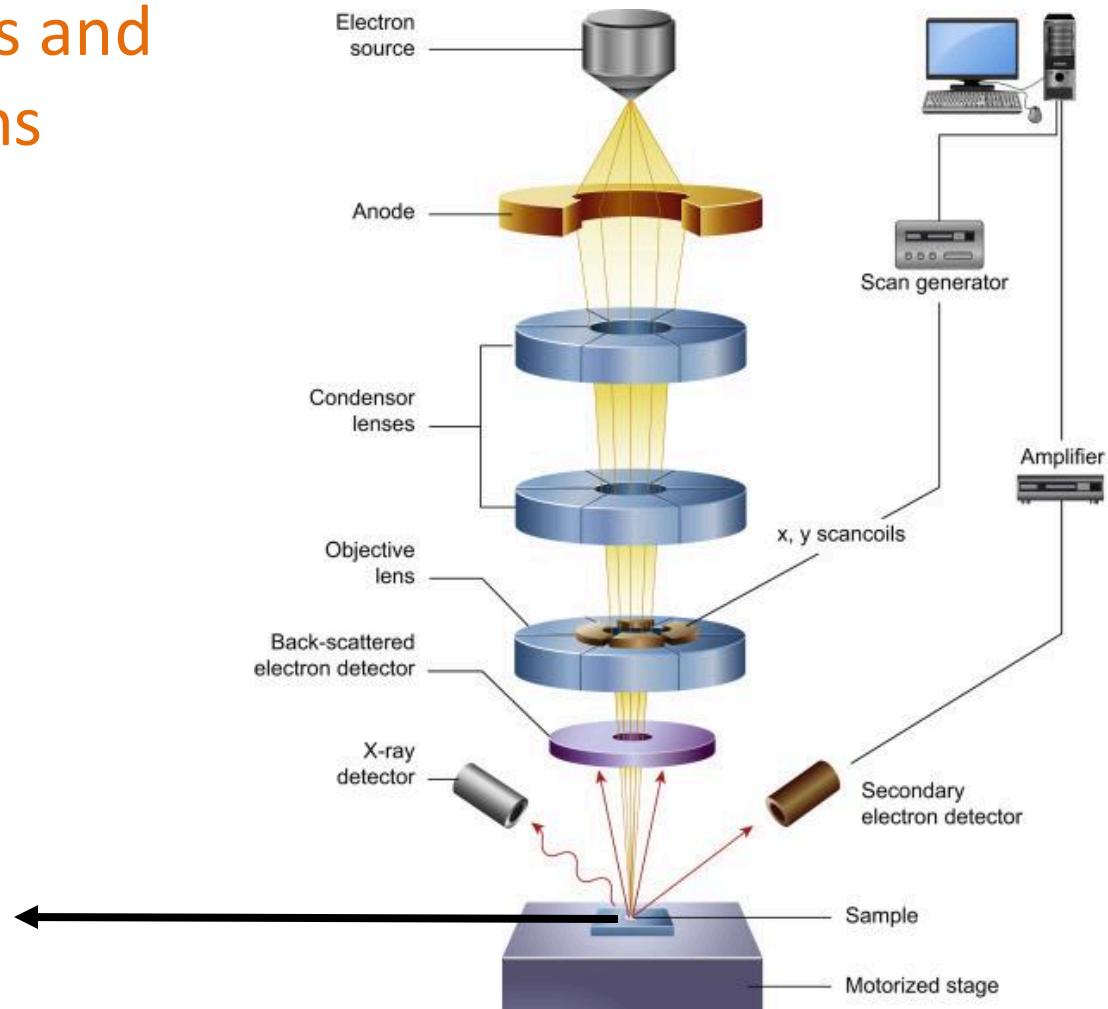
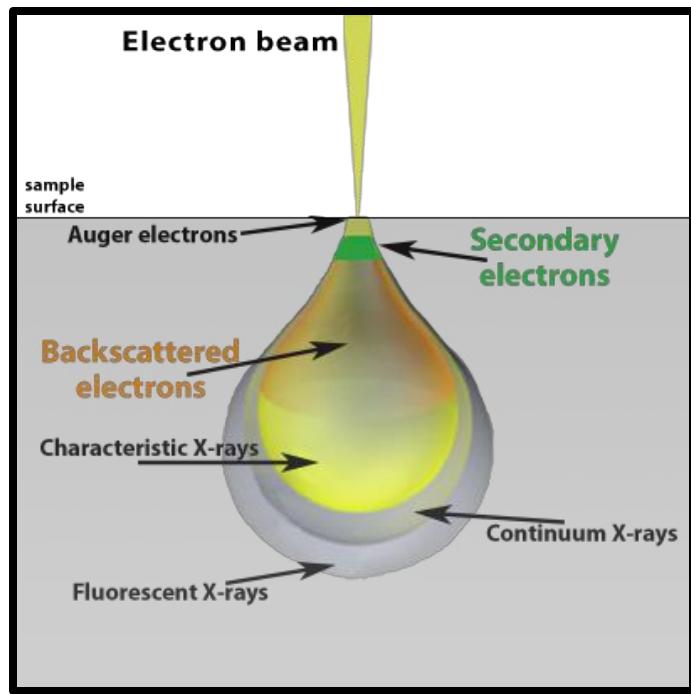


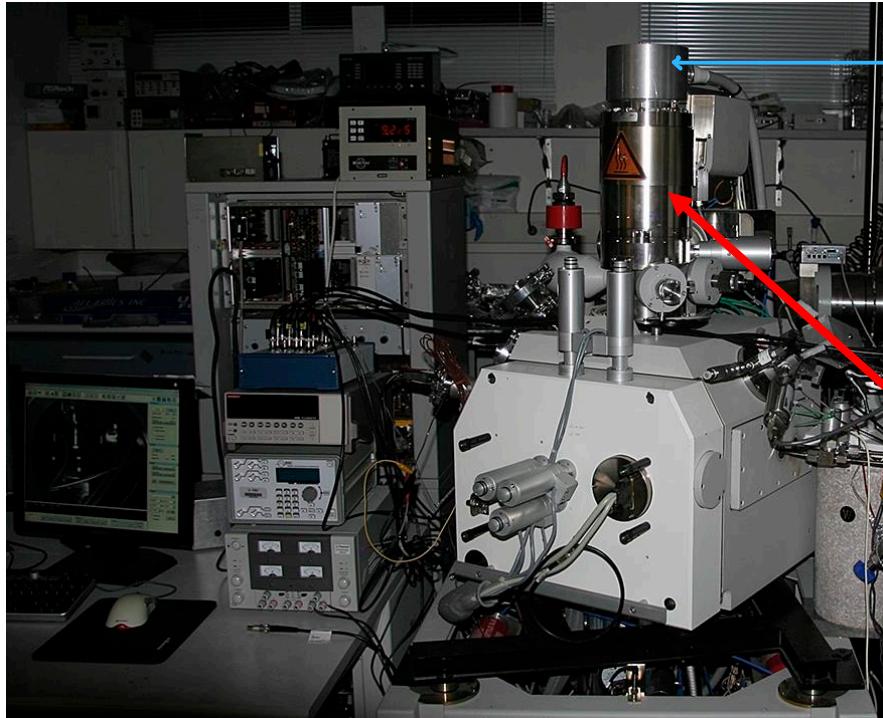


68320 Nanofabrication and Nanocharacterization Techniques

Lecture 2: Electron Optics and Electron-Solid Interactions

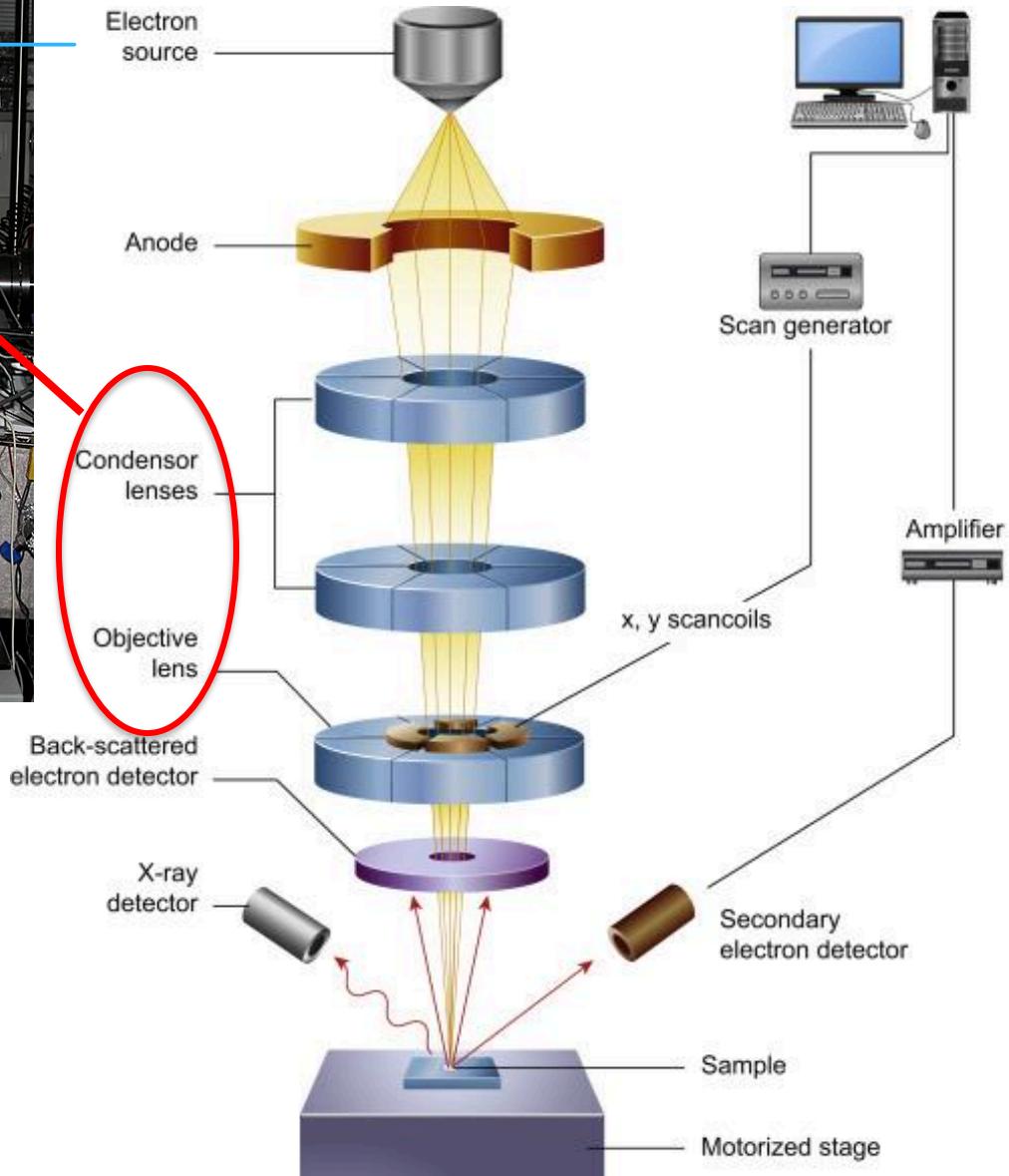


Electromagnetic lenses

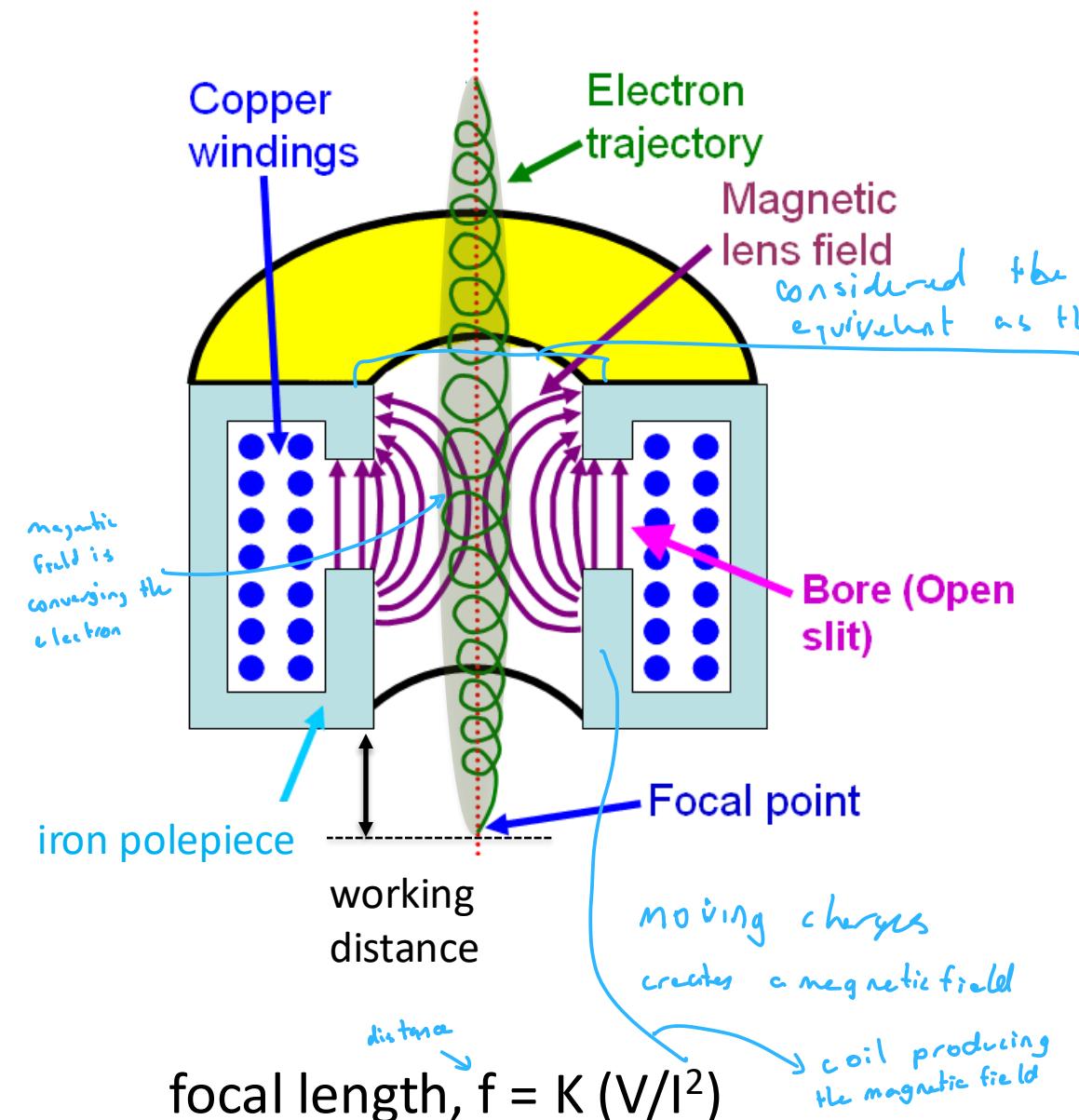


electromagnetism used to focus the
electron beam
↳ magnetic field

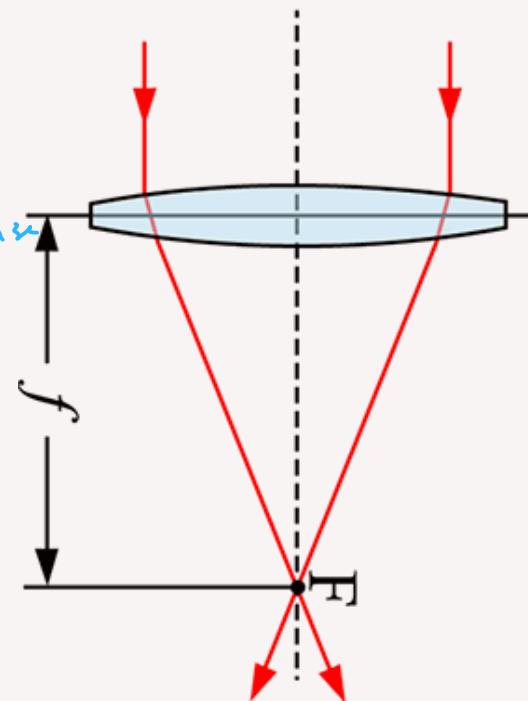
NOTE: For clarity/simplicity, this
column schematic does not show
apertures (which are discussed later)



Electromagnetic lens

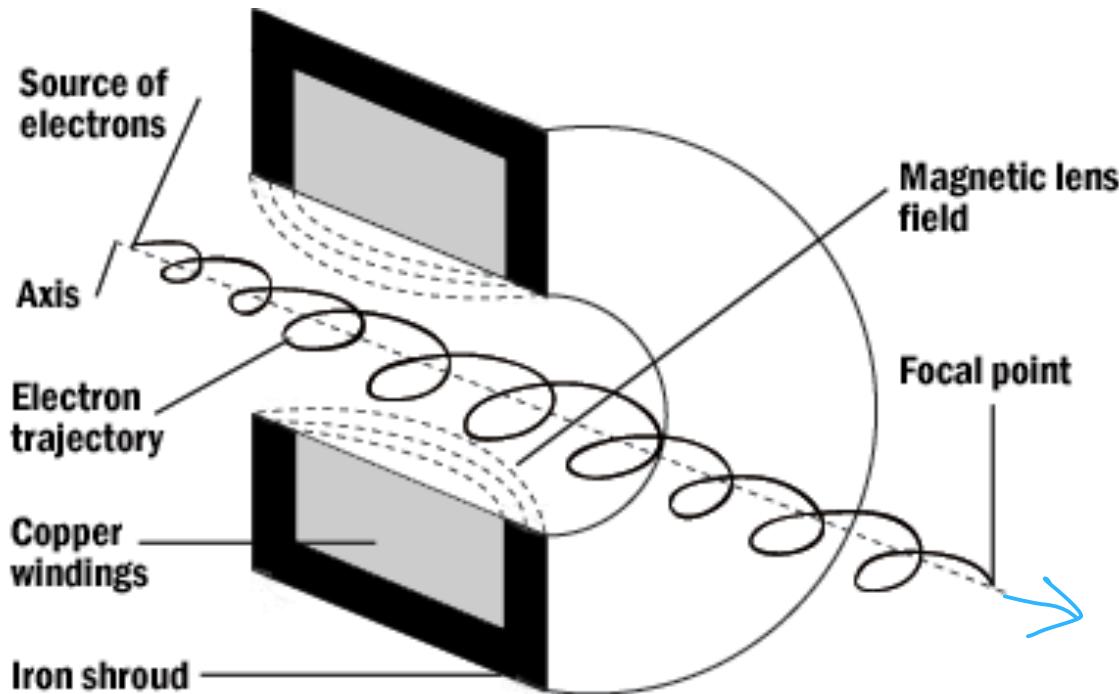


REVISION: light optics



lens: glass, refractive index n
focal length, f : fixed (sample is moved up/down to focus)

Electromagnetic lens: Electron trajectories



Force exerted on an electron:

$$\mathbf{F} = q \mathbf{v} \times \mathbf{B}$$

go to wiki for revision on basic
electrostatics



used to focus on the sample
by changing the area the beam is
focusing on

\mathbf{F} = force on a charged particle (electron) N

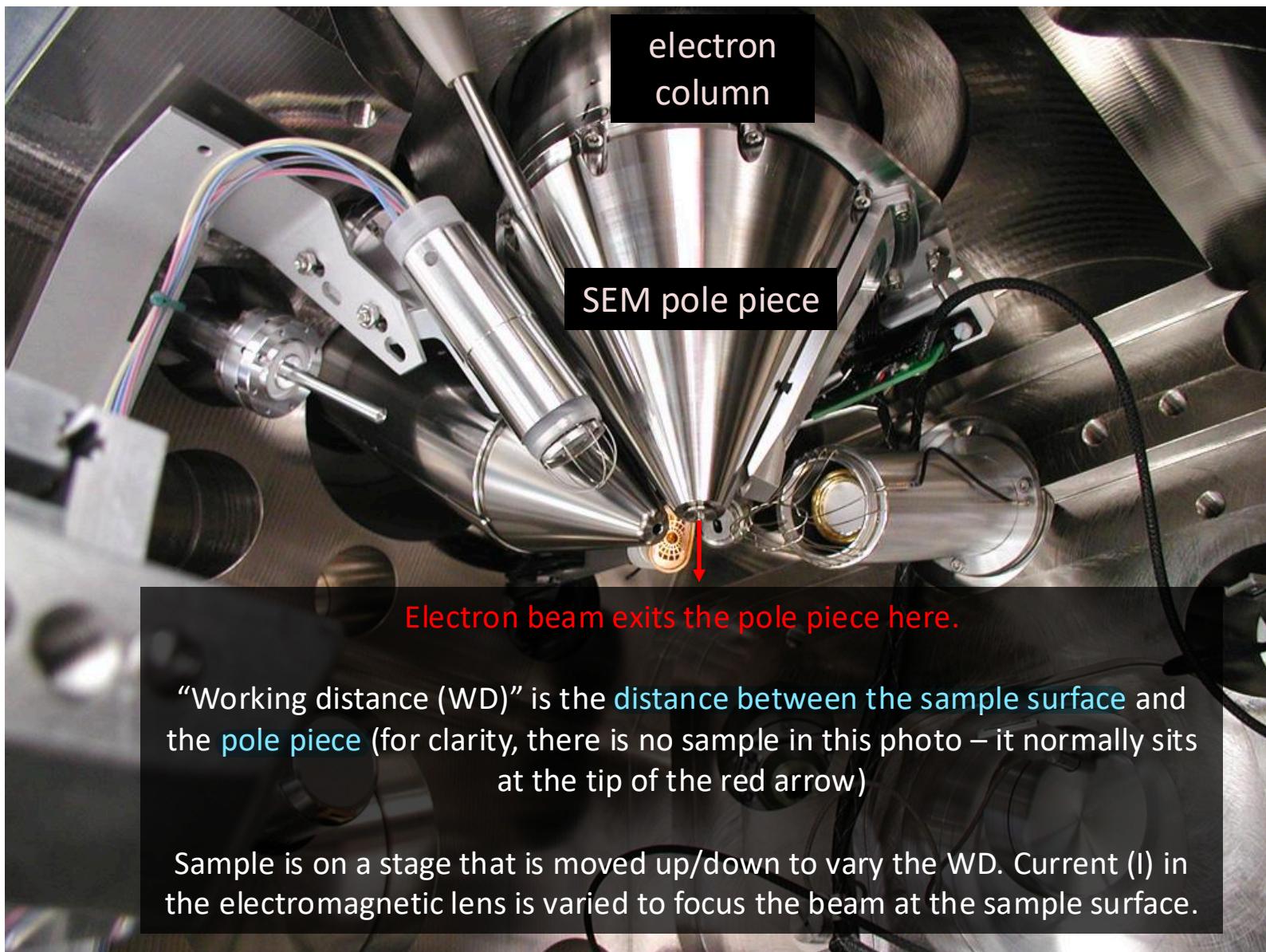
q = charge (of an electron) C

v = velocity (of electron) m/s

B = magnetic field T

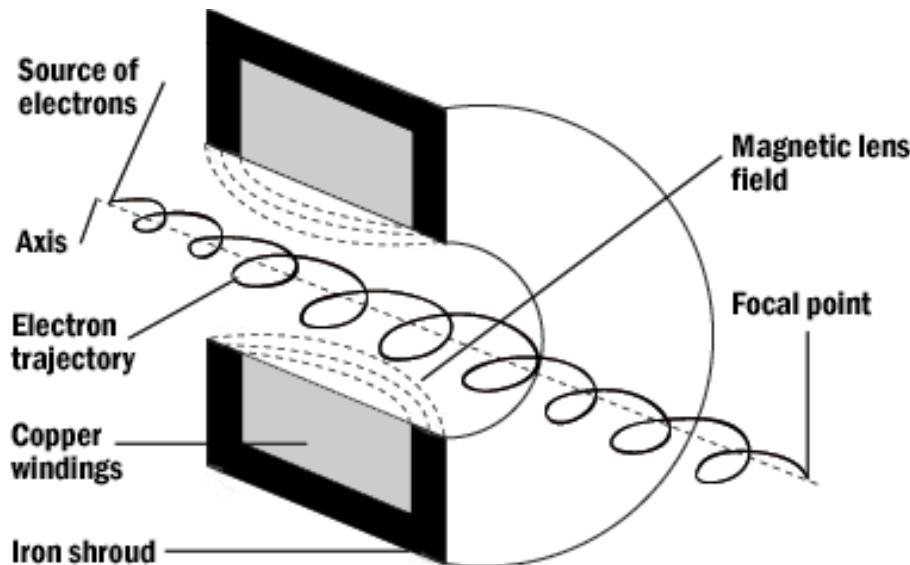
Working distance

Inside view of an SEM sample chamber



Sample class test question

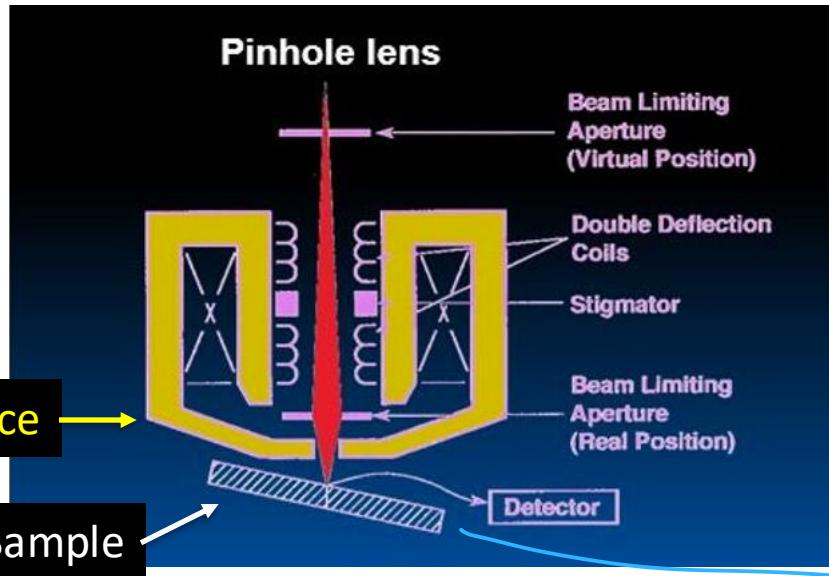
similar to class test
question



The image shows the trajectory of an electron passing through an electromagnetic lens. **Which statement is correct?**

- a) The field increases the energy of the electron.
- b) The field increases the velocity of the electron.
- c) The field increases the momentum of the electron.
- d) The field does not change the electron energy.
- e) The field decelerates the electron.

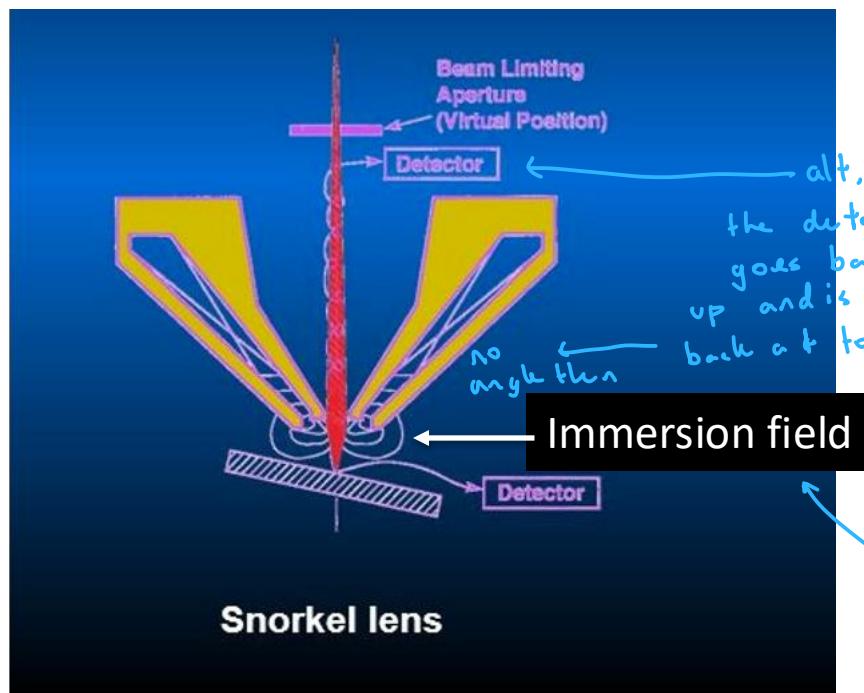
Electromagnetic lens designs



- cheaper, more basic

Pinhole lens

Magnetic field that focuses the beam is inside the pole piece.



minimise the focal length

angled to point sample to
the detector
↳ there is a bias on the
detector

Immersion lens (a.k.a. snorkel lens)

Magnetic field extends beyond the pole piece, and “immerses” the sample. This reduces the effective working distance, reduces aberrations and improves resolution.

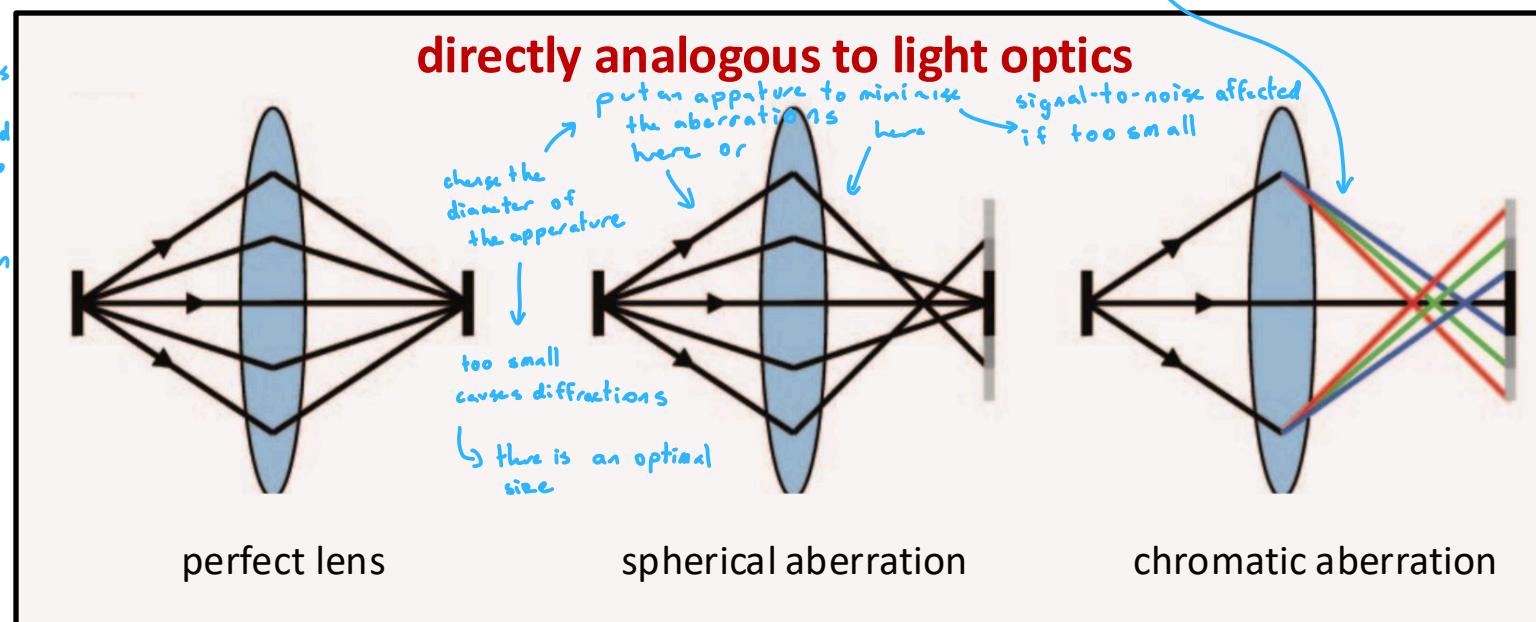
magnetic sample is BAD!

Electromagnetic lens: Aberrations

- convergence angle affects the aberrations

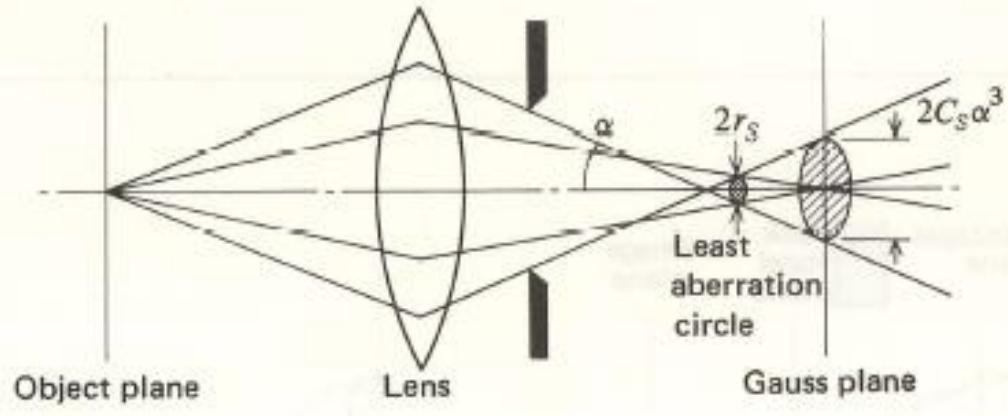
As with all lenses, electromagnetic lenses are subject to lens aberrations which increase the effective diameter of the probe - lowering spatial resolution

- **Spherical aberration:** electrons near the edge of the lens need to be focused more strongly than those near the centre
- **Chromatic:** due to thermal contributions, electrons emitted from the source are not all at the same energy (wavelength) so there is a spread of focus (reduce the energy produced in the tip)
emitter \rightarrow const. temp
minimise the aberrations)
- **Diffraction:** electrons being wave-like, small apertures can broaden the probe via diffraction effects (atoms oscillate from temp causing collision of electron, changing the velocity)
Wavelength of the electron, like the double slit experiment
 \hookrightarrow aperture causes the wavelength to diverge around (in picometres))
- **Astigmatism:** lack of radial symmetry of lens - non-circular probe
when beam is not the right shape \rightarrow from circle to ellipse shape
diff energies/ wavelengths



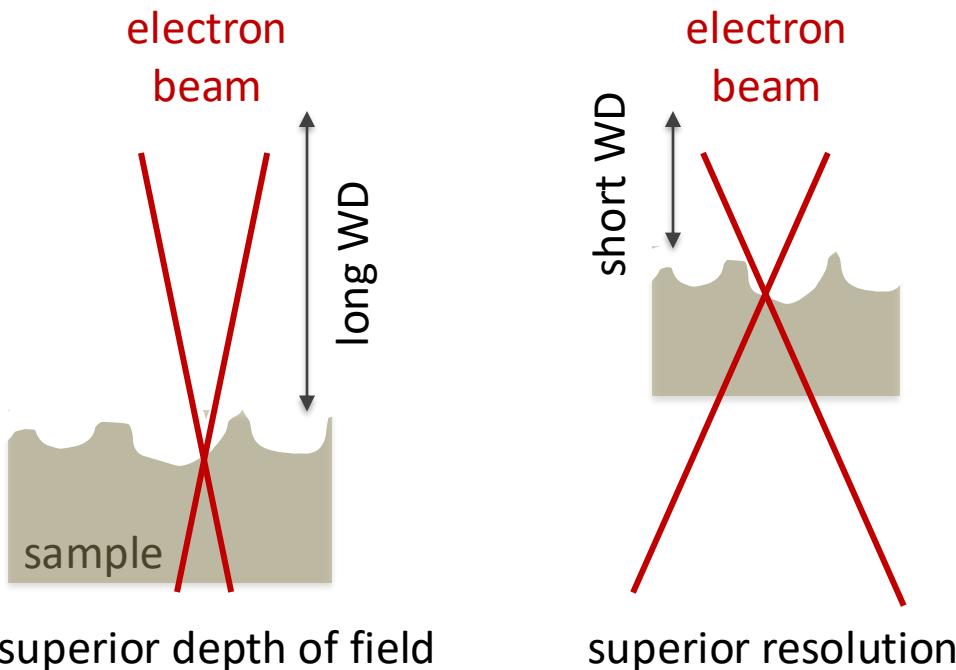
Spherical aberration, C_s

aperture: rejects (blocks) high angle electrons



C_s reduced by decreasing aperture diameter, which also limits the electron beam current.

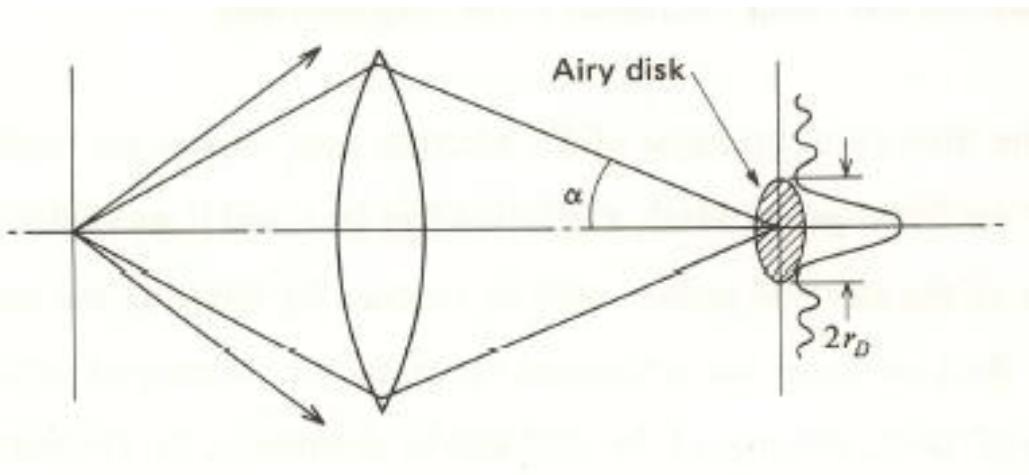
An SEM operator can use the aperture size to control resolution and electron beam current.



C_s is also reduced by increasing the magnetic field of the electromagnetic lens (ie: by increasing the beam convergence angle and operating the SEM at short “working distance”, WD).

An SEM operator can use the working distance to trade off resolution for depth of field.

Diffraction aberration

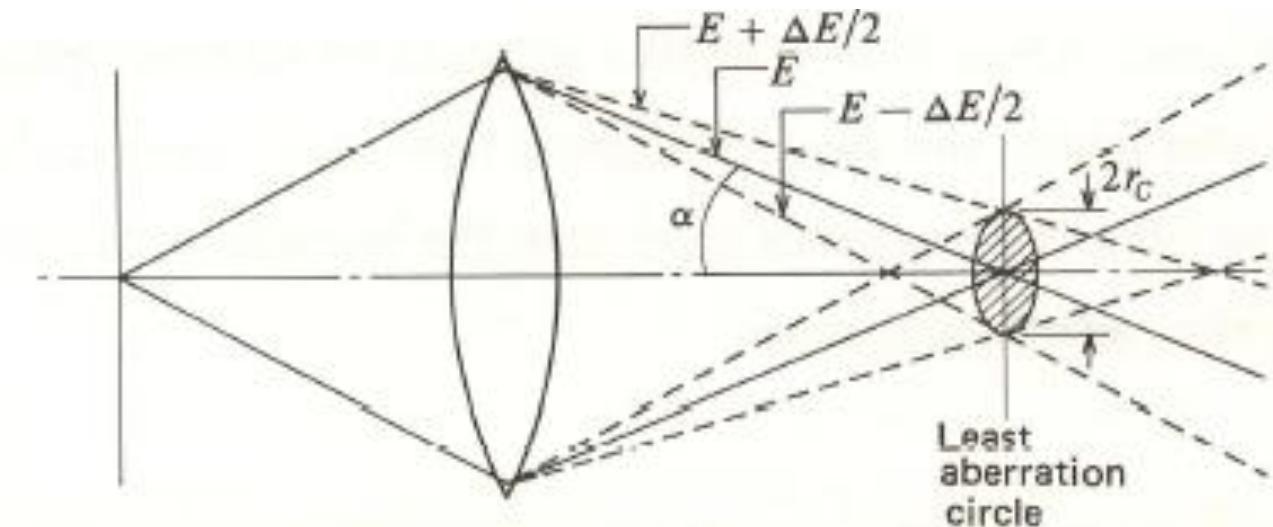


As the aperture diameter decreases, electrons will diffract due to their wave-like properties

r_D reduced by increasing aperture diameter (i.e., if the aperture is too small, resolution is limited by diffraction)

there is an optimum aperture diameter (typically $\sim 10 \mu\text{m}$ in an SEM) that yields best resolution (ie: smallest electron beam diameter) by optimising both diffraction & spherical aberrations

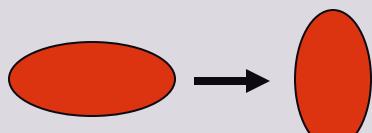
Chromatic aberration, C_c



- Electrons have a range of energies due to the temperature of the electron source (and also fluctuations in the accelerating voltage caused by noise in the power supply)
- Examples: cheap W electron gun: 1 eV to 3 eV; cold field emission gun: ~ 0.3 eV

Astigmatism aberration

Astigmatism Present

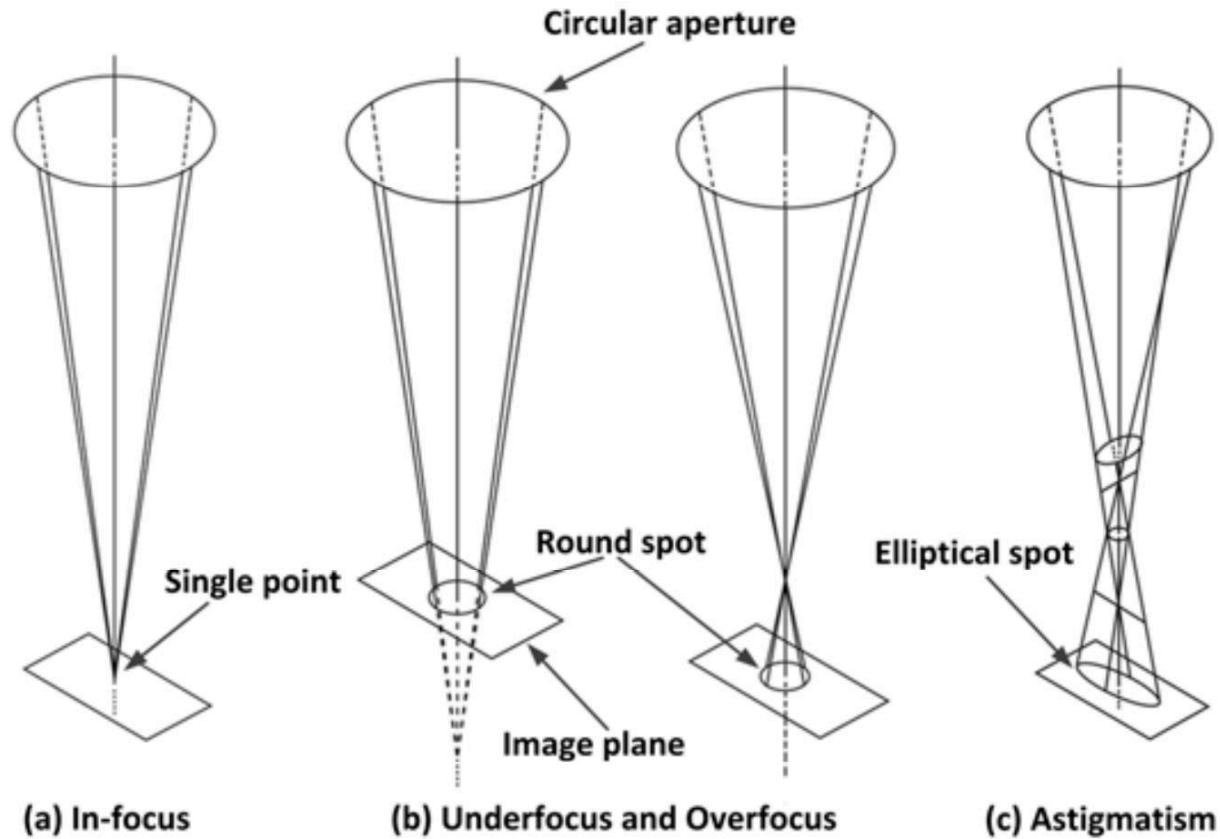


rocking focus

Astigmatism Corrected

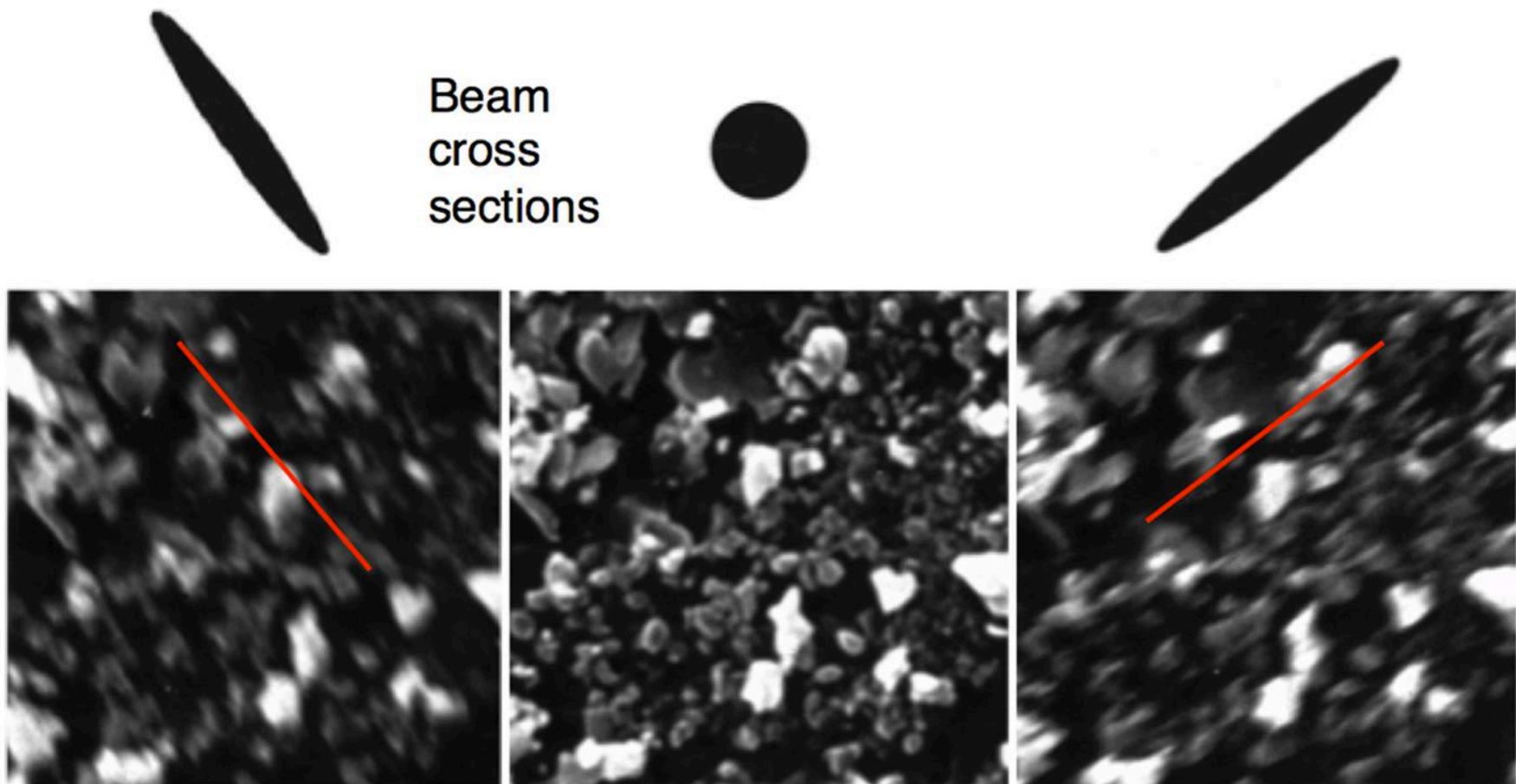


rocking focus



electrodes around the beam in x or y
to change the shape of the beam

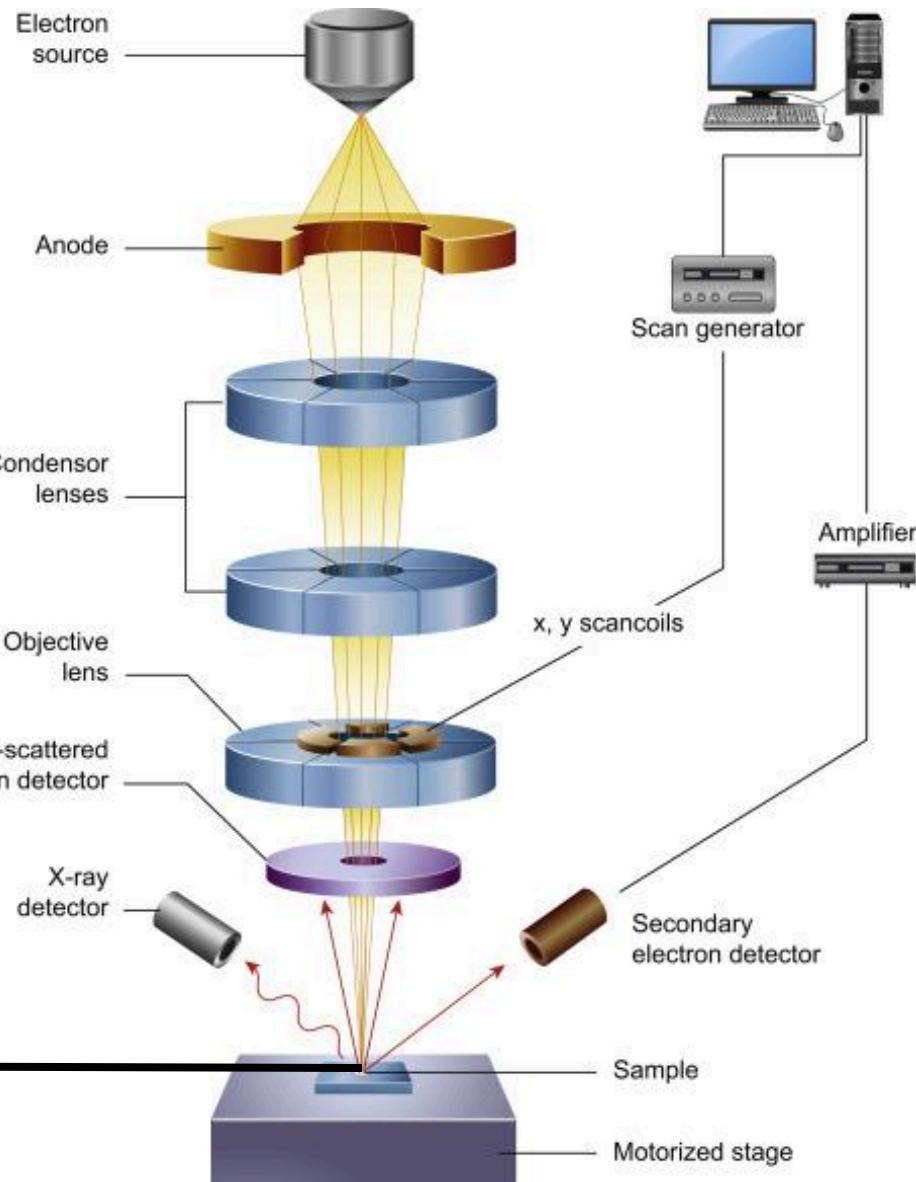
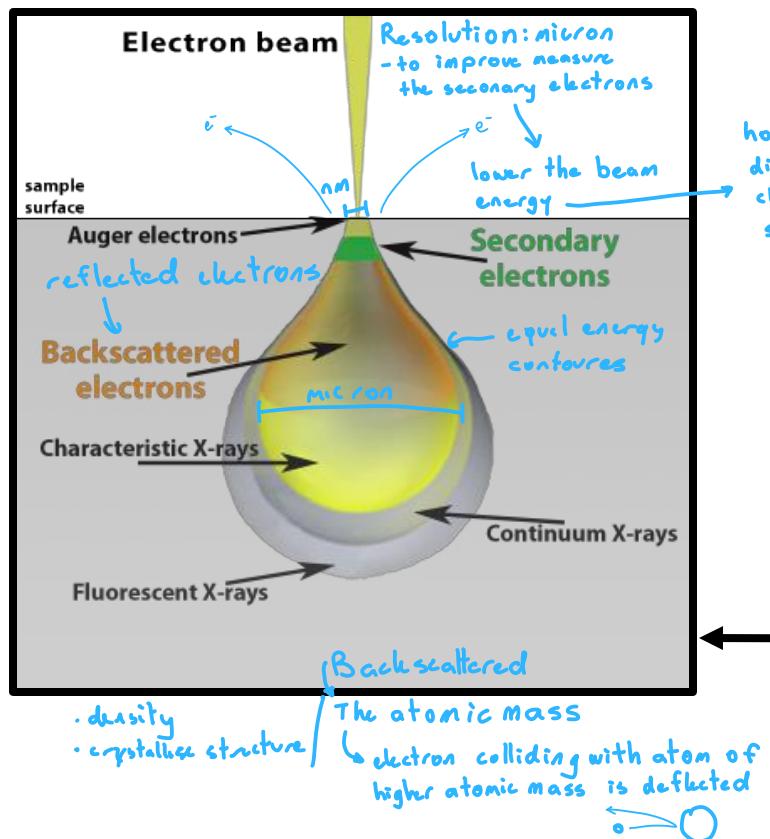
Astigmatism aberration



- caused by lack of radial symmetry in the lens
- produces an elliptical electron beam spot rather than circular
- identified by 90° streaking as image rocked through focus
- corrected by stigmators that re-shape beam to a circular spot – either r, θ or x, y control to adjust orientation and strength of the correction field

Electron imaging & electron-solid interactions

electron-solid interactions affect
electron image:
• resolution &
• information content

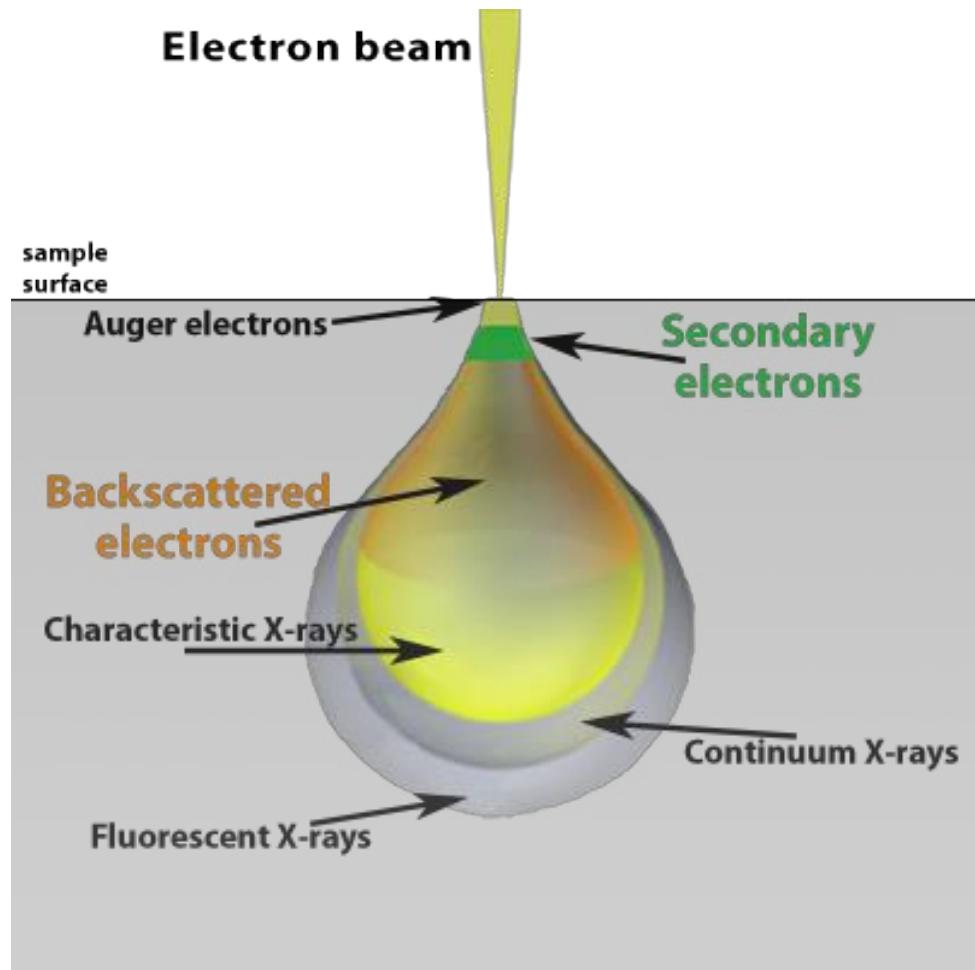


Interaction of the electron beam/probe and the sample

this is covered in this week's tutorial

- the total energy of the incident electrons must be dissipated (in a bulk specimen) and energy must be conserved
- energy loss processes generate emission signals that can be used to form an image as the electron beam scans across the specimen
- each of these signals carries different information about the specimen

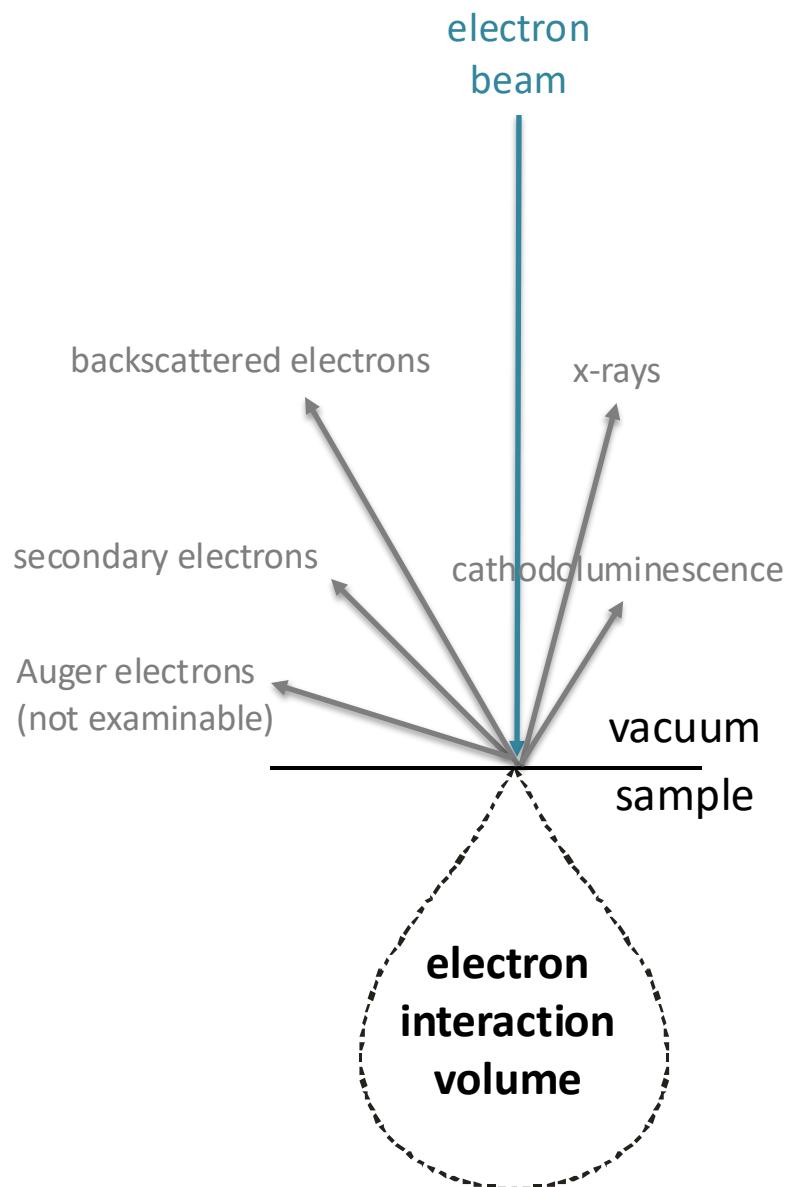
Each emissive signal originates from a different depth within the specimen



Main energy loss processes in solids

this is covered in this week's tutorial

- **specimen heating** - generation of **phonons** - highest cross-section
- **breaking of chemical bonds that bind atoms** (1 -10 eV): produces **secondary electrons** and **cathodoluminescence**
- **ionization of core shell electrons** (keV): produces **X-rays**



Electron Scattering Mechanisms

Elastic Scattering (due to interactions with nuclei)

Change in electron trajectory with virtually no loss in energy

Causes electron spreading in specimen & backscattered electrons

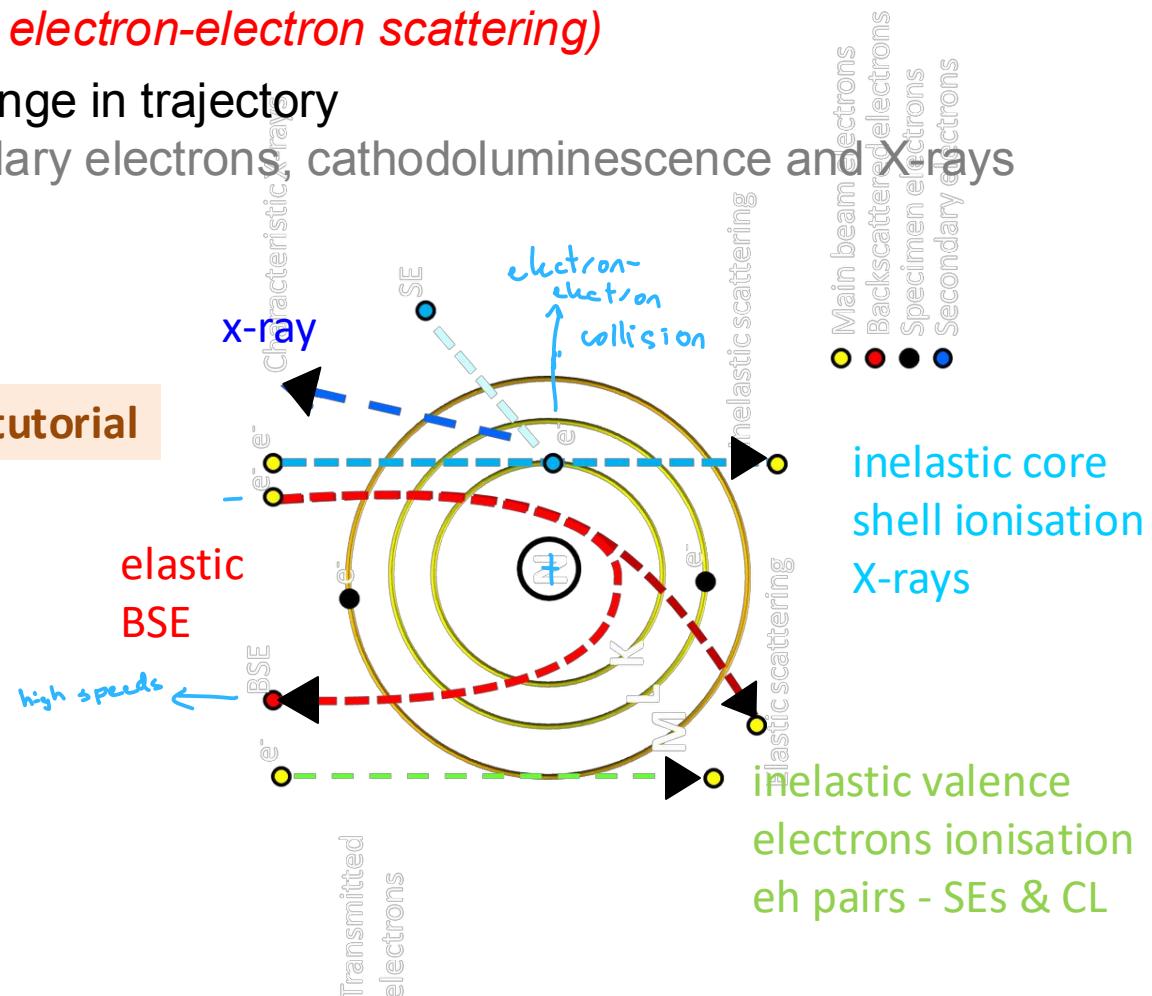
Inelastic Scattering (due to electron-electron scattering)

Loss of energy with no change in trajectory

Generation of heat, secondary electrons, cathodoluminescence and X-rays

this is covered in this week's tutorial

Illustrates
the types of →
collisions



Primary (“beam”) electron range (R_e)

this is covered in this week's tutorial

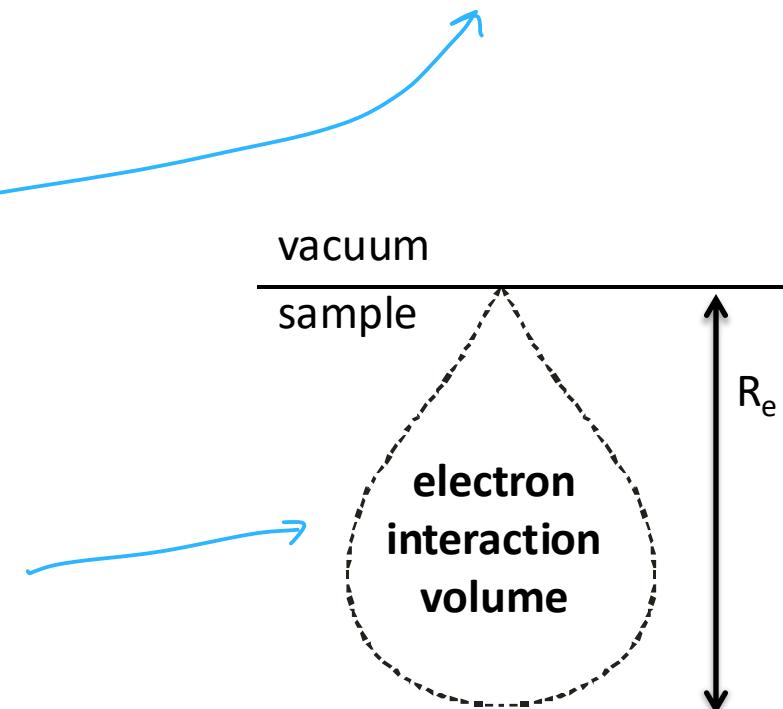
$$R_e(nm) = \frac{27.6 A E_o^{5/3}}{Z^{8/9} r}$$

atomic weight [g/mol]

atomic number

density g/cm³

energy of beam [keV]



Electron emission: Backscattered Electron (BSE) imaging in Scanning Electron Microscopy (SEM)

Papers on Canvas (useful for today's tute)

\Canvas\Modules\Tutorials...\Tute 2...\07. CASINO - intro.pdf

Dashboard
Announcements
Modules
Assignments
Discussions
People
Student Feedback
Survey
Search
Grades
Quizzes
Files
Rubrics
Pages
Outcomes
Syllabus
Collaborations
Settings

LITERATURE

The following articles are provided as PDFs, and will be referred to by th

[01A. FIB1.pdf](#) ↓
[01B. FIB2.pdf](#) ↓
[02. SEM - Low Voltage.pdf](#) ↓
[03. cathodoluminescence.pdf](#) ↓
[04. FIB and 3D SEM imaging.pdf](#) ↓
[05. EDX Mapping.pdf](#) ↓
[06. SEM Resolution.pdf](#) ↓
[07. CASINO - intro.pdf](#) ↓
[08. CASINO - 3D.pdf](#) ↓
[09. CASINO - elastic.pdf](#) ↓
[10. CASINO - inelastic.pdf](#) ↓
[11. Gas-assisted nanofab - SEM and FIB.pdf](#) ↓
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[19. FIB - TEM sample prep.pdf](#) ↓

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Original Papers

CASINO : A New Monte Carlo Code in C Language for Electron Beam Interaction —Part I: Description of the Program

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Département de Génie Mécanique, Université de Sherbrooke, Sherbrooke, Québec, Canada

Summary: This paper is a guide to the ANSI standard C code of CASINO program which is a single scattering Monte Carlo SImulation of electroN trajectory in sOlid specially designed for low-beam interaction in a bulk and thin foil. CASINO can be used either on a DOS-based PC or on a UNIX-based workstation. This program uses tabulated Mott elastic cross sections and experimentally determined stopping powers. Function pointers are used for the most essential routine so that different physical models can easily be implemented. CASINO can be used to generate all of the recorded signals (x-rays, secondary, and backscattered) in a scanning electron microscope either as a point analysis, as a linescan, or as an image format, for all the accelerated voltages (0.1–30 kV). As an example of application, it was found that a 20 nm Guinier-Preston Mg₂Si in a light aluminum matrix can, theoretically, be imaged with a microchannel backscattered detector at 5 keV with a beam spot size of 5 nm.

Key words: Monte Carlo simulation, low-energy scanning electron microscope, backscattered electrons, image simulation, line profiles, x-rays φ(pz) computation, Mott elastic cross section, experimental stopping power

1. Introduction

Nowadays, new compounds and alloys are designed to answer specific needs and specific applications. In general, the new high-strength alloys contain a very fine scale microstructure, less than micrometer scale grain size, and precipitates < 0.05 μm. The development of such new materials must be followed by both crystallographic and chemical characterization to yield a full understanding of the microstructure and property relationships. In this perspective, electron microscopy (scanning and transmission) is the most complete and power-

ful instrument that could be used. Scanning electron microscopy (SEM) has the advantage that sample preparation is generally more straightforward compared with the preparation of the electron transparent region needed for the transmission electron microscope (TEM).

Combining a field emission source into an SEM (FESEM) results in a high current density into a very small probe (1nm @ 30 keV). The FESEM can be used efficiently to characterize the new high-strength alloys as well as complex semiconductor multilayers. In addition, the FESEM opens new opportunities for imaging and microanalysis at low voltage (<5 kV) such as the examination of non- or poorly conducting materials (Joy and Joy 1996), the imaging dopant concentration in semiconductor (Perovic 1995), quantitative x-ray analysis with resolution < 100 nm, and the imaging of phases < 20 nm (Gauvin *et al.* 1995a). Traditionally, Monte Carlo programs are used to exploit and understand fully the capabilities of electron microscopes (Newbury and Yakowitz 1975) at energy > 10 keV. However, for low energy (E < 5 keV), because the first Born approximation is no longer valid, a new generation of Monte Carlo programs is urgently needed. A careful investigation of electron-solid interaction models must be developed before any conclusion can be given.

In this paper, we fully describe a complex Monte Carlo program specifically designed for low-beam interaction that can be used to generate all of the recorded signals (x-rays, secondary and backscattered) in an SEM. This program can also be efficiently used for the range of acceleration voltage found on an FESEM (0.1–30 kV). The goal of this paper is to provide users with a complete description of the most important procedures and features of this Monte Carlo program. Description of the available physics will also be presented. In addition, a full description of the most important routines will be given. This section is more programmer-oriented. As an example of application, the possibility of imaging < 100 nm Mg₂Si precipitates in an aluminum matrix (Al 6061 alloy) will be presented. The sources code and the executable file is now available on the Internet at the address <http://casino.gme.usherfb.ca/casino>

Address for reprints

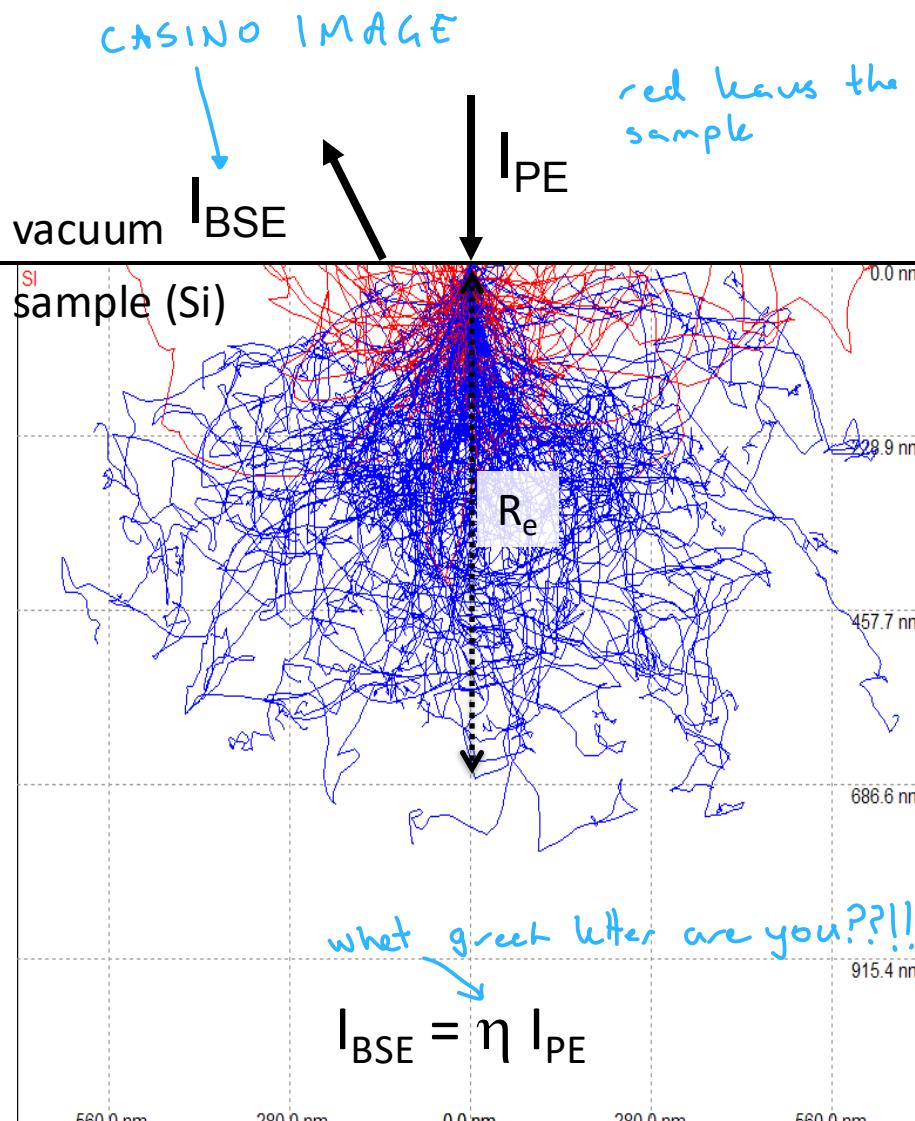
Pierre Hovington
Département de Génie Mécanique
Université de Sherbrooke
2500 Boulevard Université
Sherbrooke, Québec
Canada, J1K 2R1

2. Features of the Program

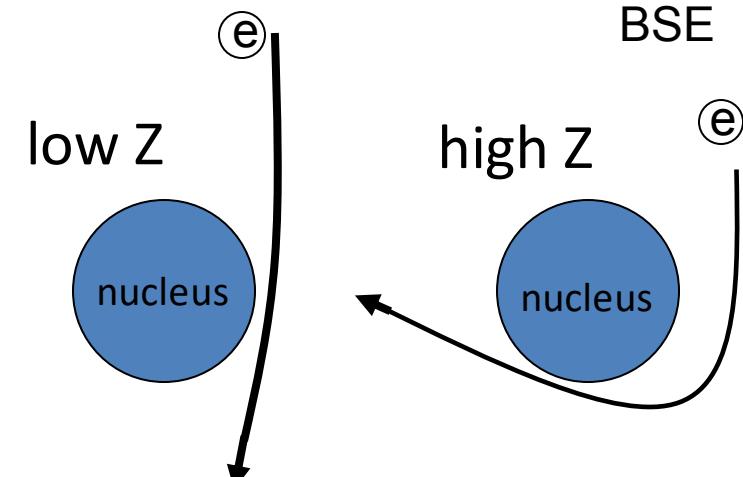
This Monte Carlo program contains over 50,000 lines of code in ANSI standard C language distributed over 20 files. It

Backscattered Electrons: compositional imaging

this is covered in this week's tutorial



Red trajectories are primary electrons that have been back-scattered out of the specimen.



larger Z increases the electron scattering efficiency, so η increases with mean Z

η is the BSE yield

BSE compositional Imaging

this is covered in this week's tutorial

$$I_{BSE} = \eta I_{PE}$$

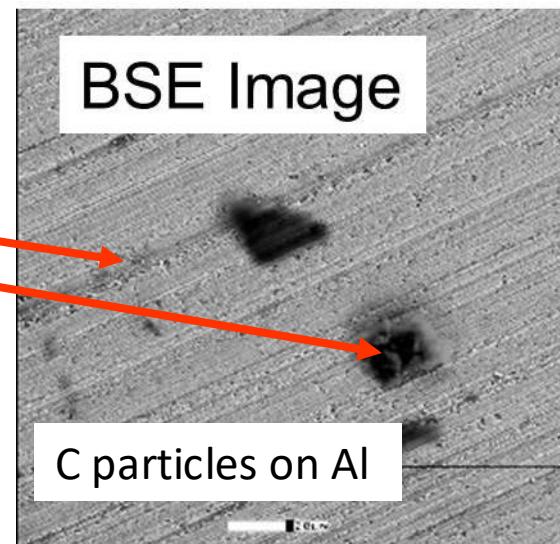
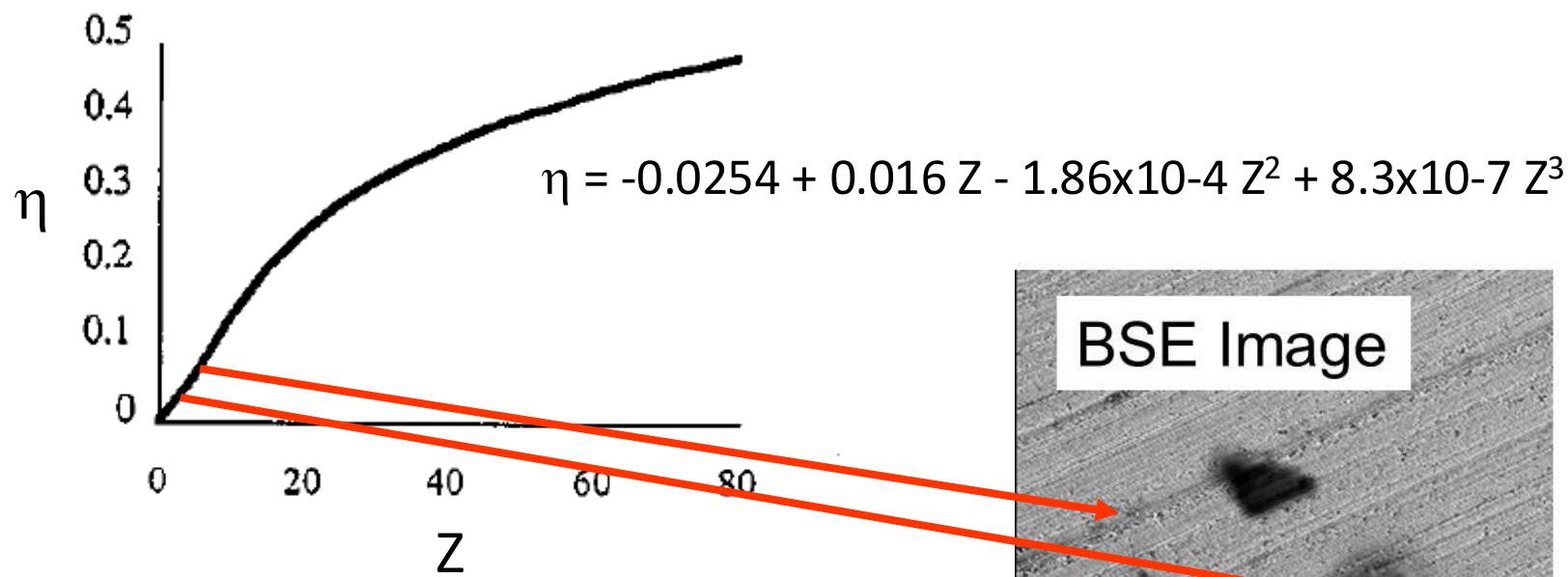
$$\eta = I_{BSE} / I_{PE}$$

I_{PE} = primary electron beam current

I_{BSE} = backscattered electron (BSE) current

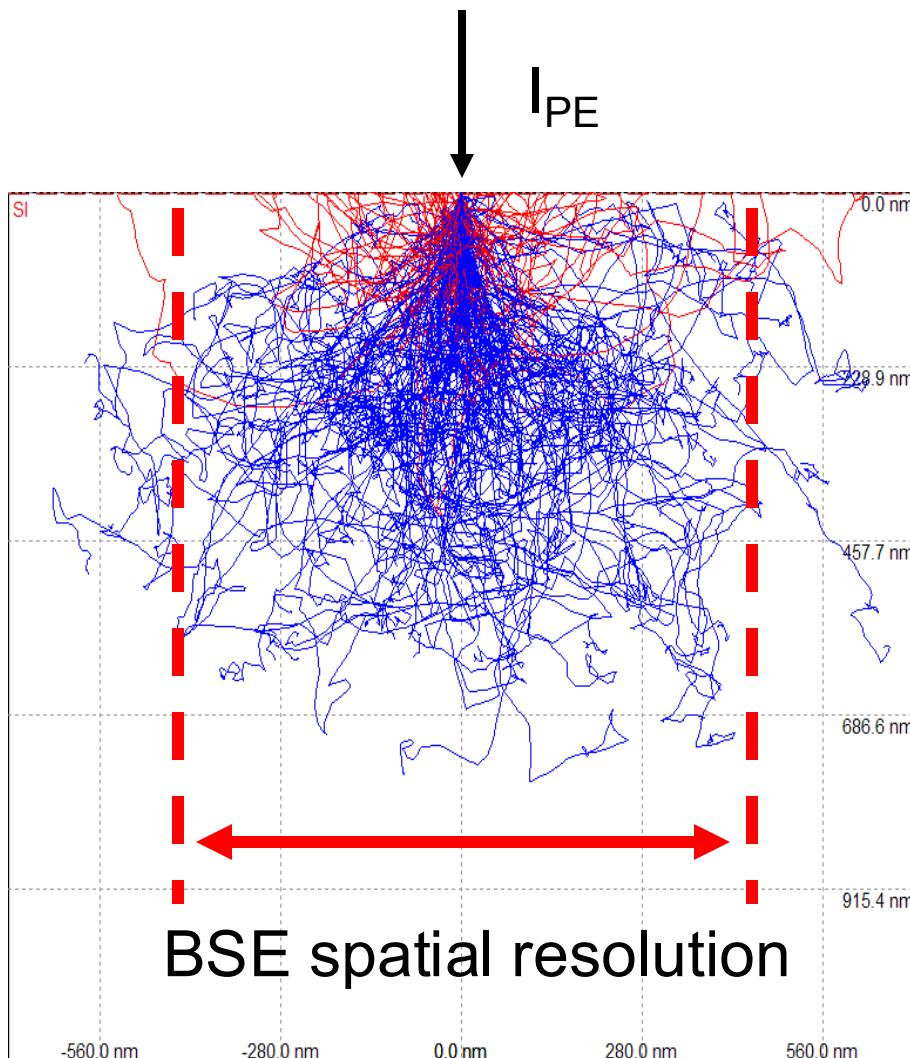
η = BSE coefficient (a.k.a. "BSE yield")

η increases with increasing atomic number (Z)



Dark carbon particles in BSE image have lower average Z than Al substrate

BSE Compositional Imaging: Resolution

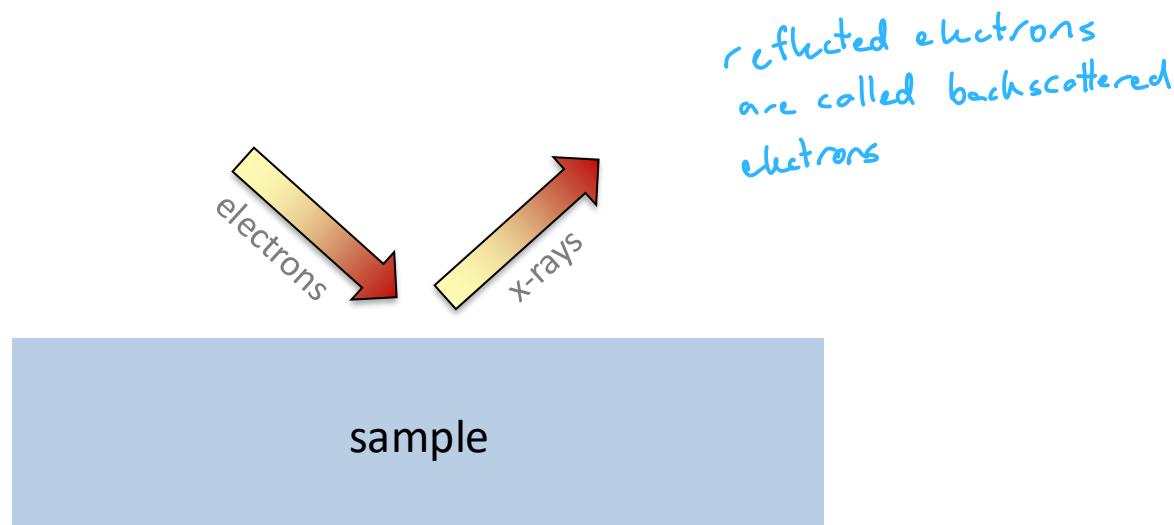


BSE image resolution is approximated by the lateral dimensions of the interaction volume rather than the electron probe diameter

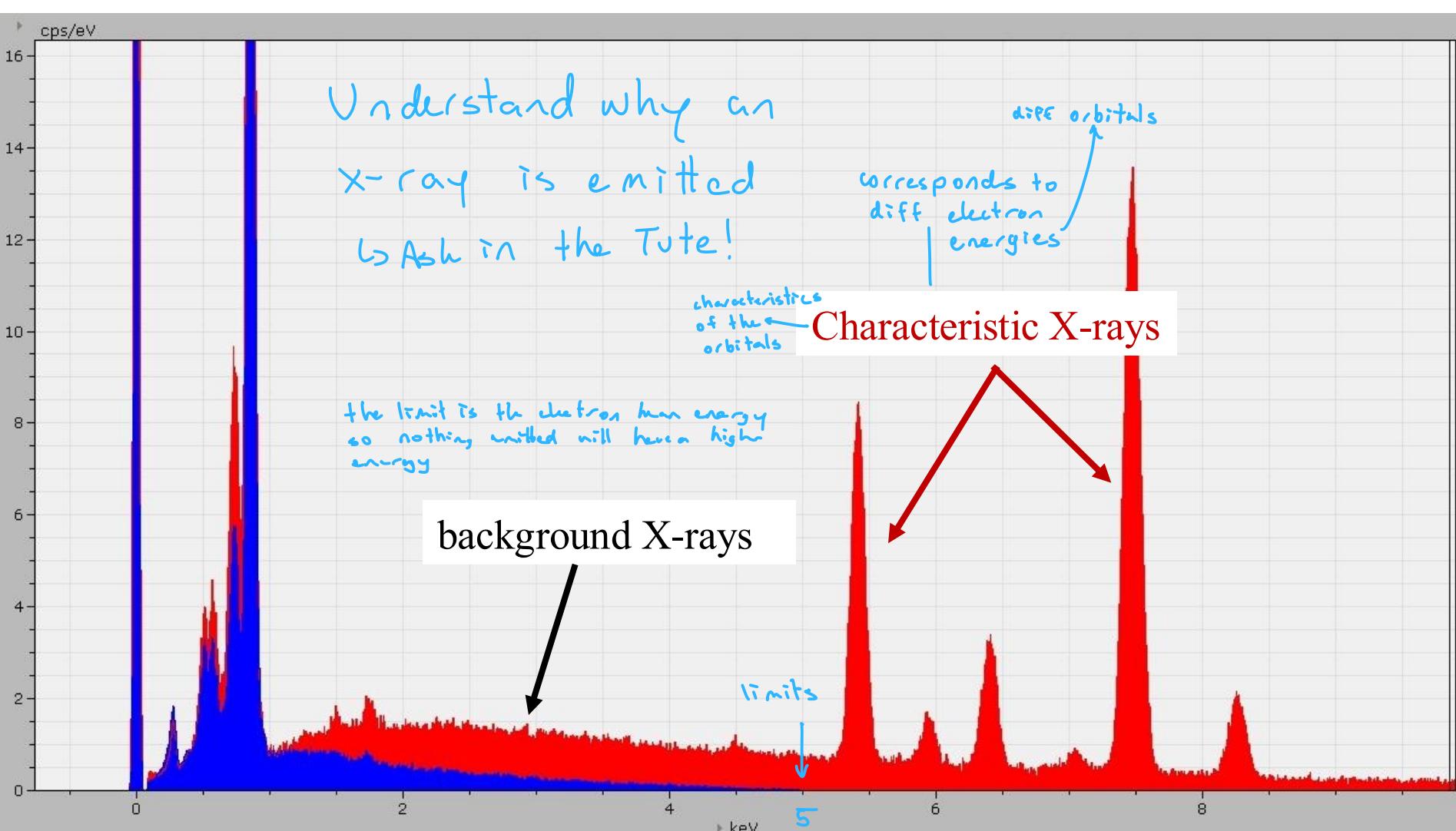
this is covered in this week's tutorial

Relevant to Week 3 & 4 (depending on which group content!)

X-ray analysis in a scanning electron microscope: Energy-dispersive x-ray spectroscopy (EDX)



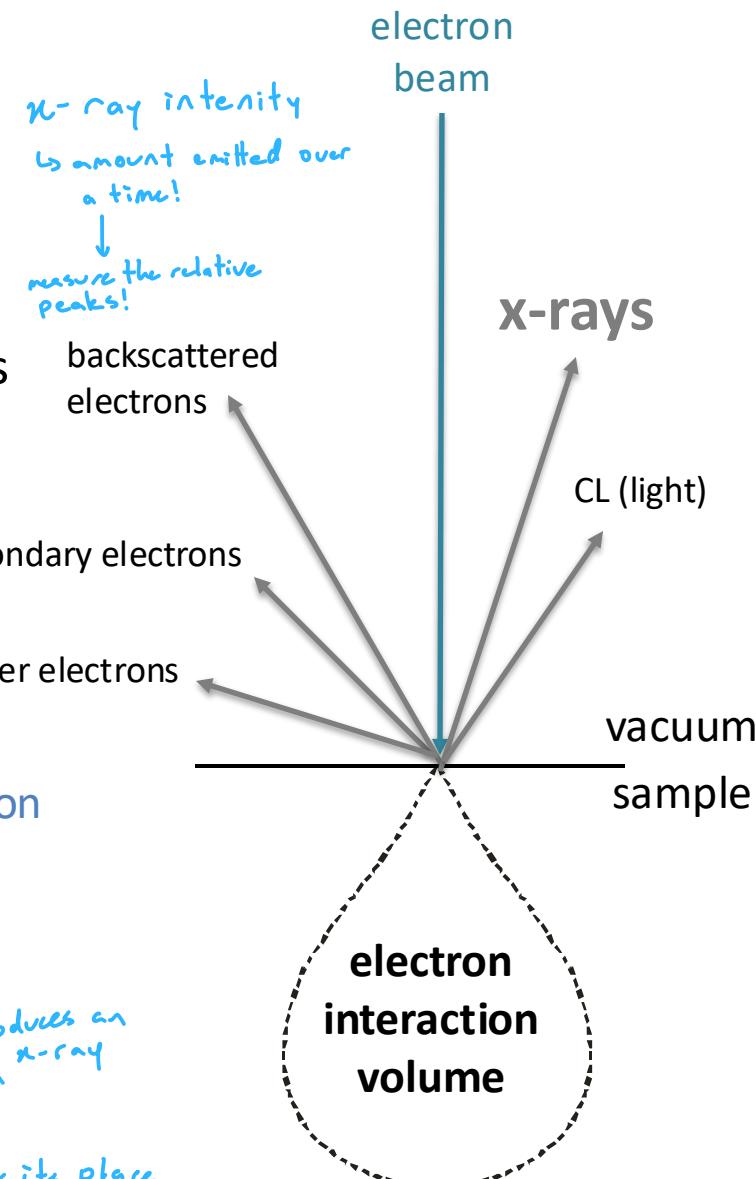
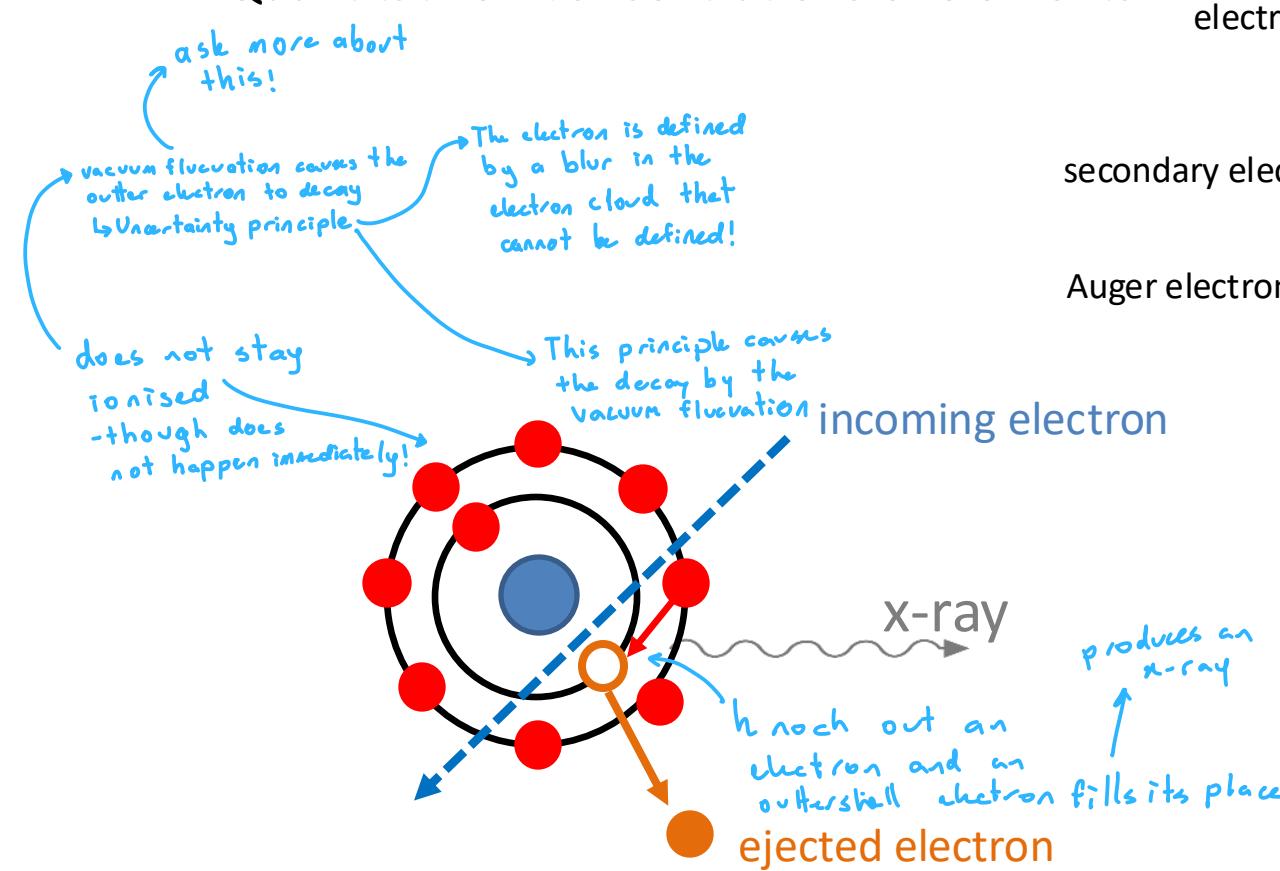
EDX of steel: 5keV (Blue) & 15 keV (red)



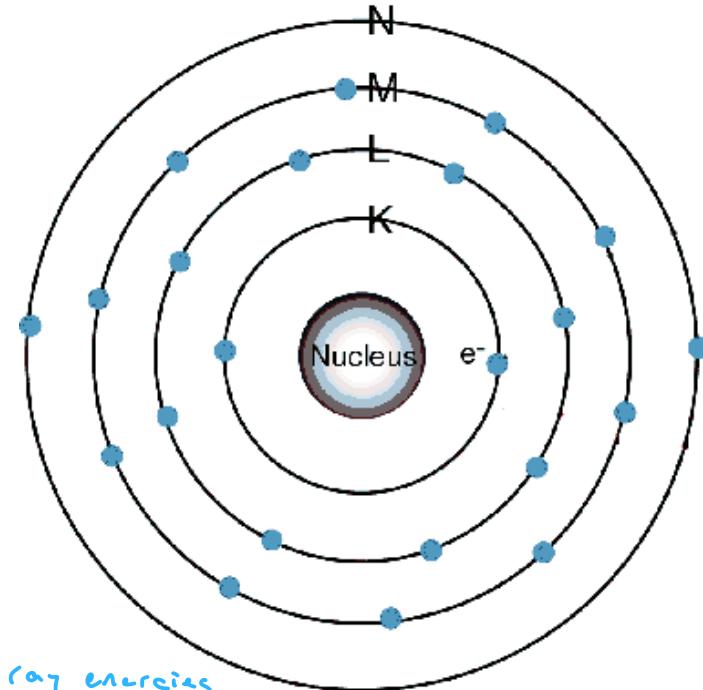
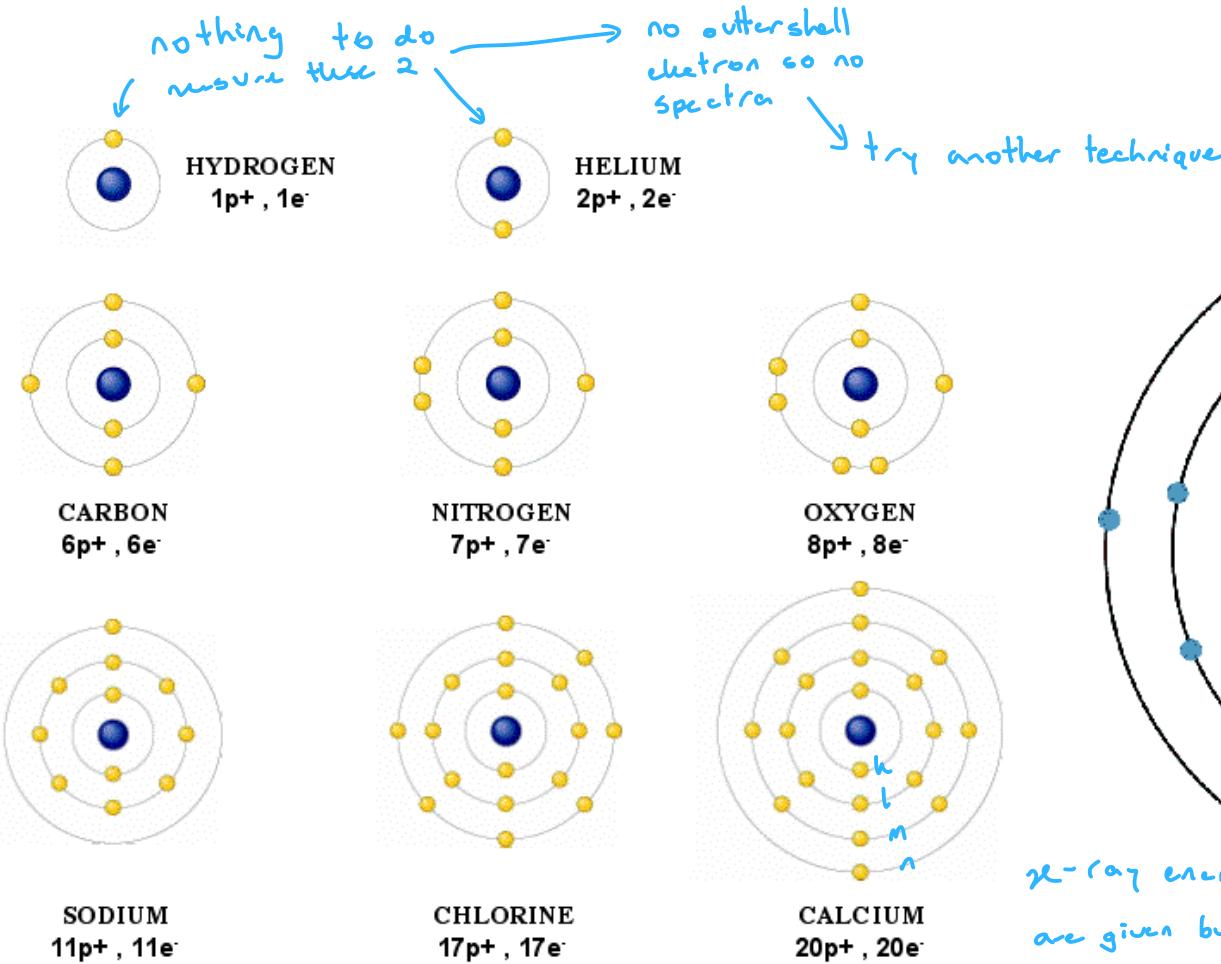
All	cps/eV	Results [Mass-% (norm.)]	Sort: Value
5 kv Inconel600.spx	0.00		
15 kv Inconel600.spx	0.24		

Characteristic x-rays: Microanalysis

- electron beam induced x-ray emission allows selective area elemental analysis down to nanoscale volumes
 - Qualitative - What elements are present
↳ but does not tell how much of it ↳
 - Quantitative - Concentrations of elements



Atomic structure



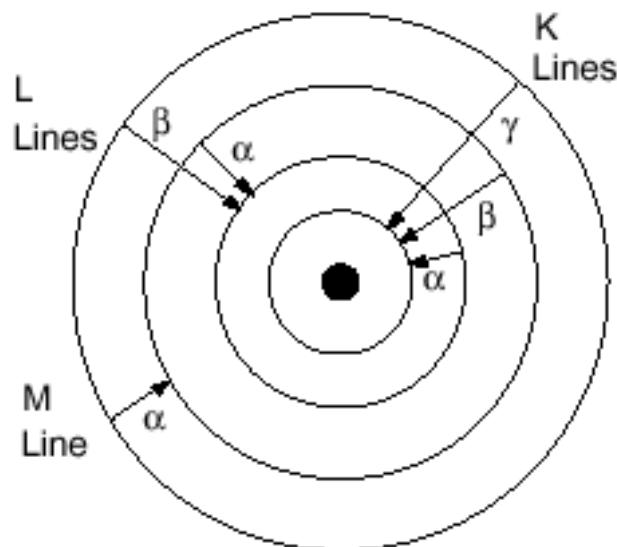
γ -ray energies
are given by energy
difference

X-ray lines are labelled K, L, M... These letters denote the orbital that is ionised (ie: the orbital that an electron transitions to upon x-ray generation)

Energy required to remove the electron from an orbital is known as the ionisation potential (a.k.a. critical edge energy, E_C) generally around 0.1 to 50 keV

Characteristic x-rays

- energy of the X-ray is determined by the energy difference between the atomic levels involved in the electronic transition
- each element has a characteristic set of X-rays and X-ray spectra can be used to identify elements from nanometer sized volumes



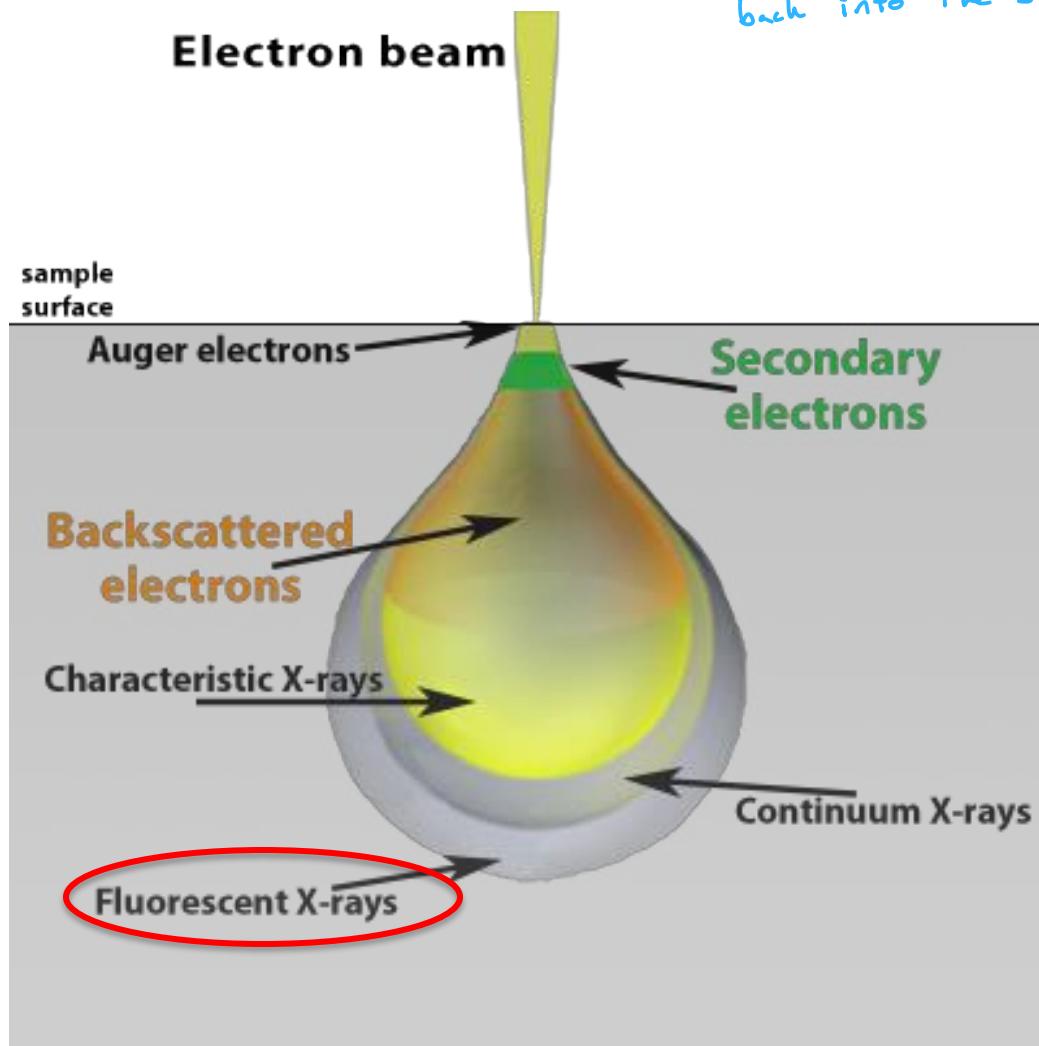
X-ray notation

K x-rays are transitions that terminate on **1s level**

L x-rays are transitions that terminate on **2s, 2p levels**

M x-rays are transitions that terminate on **3s, 3p, 3d level**

X-ray absorption (in a sample)

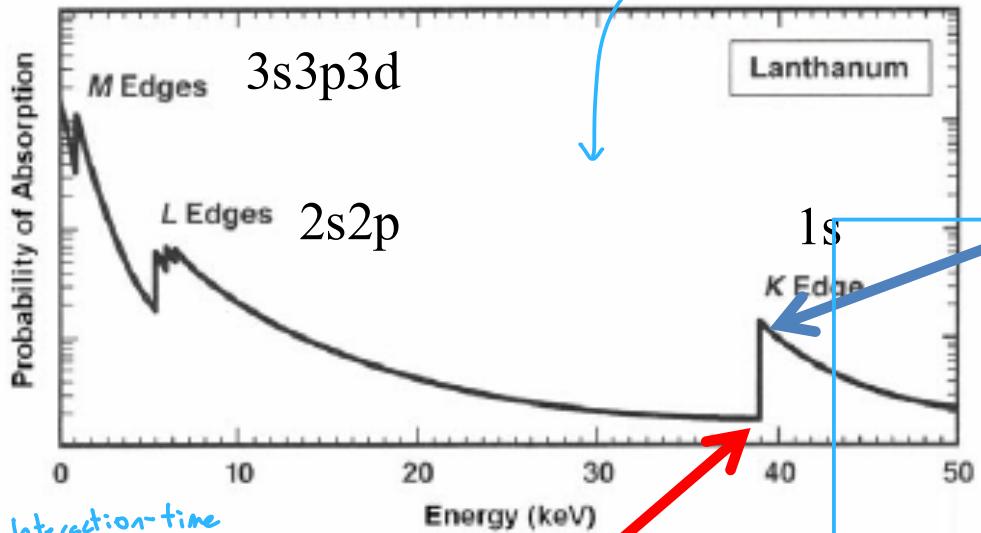


the x-rays generated within the interaction volume are absorbed by electrons as they travel through the sample

each x-ray photon is either absorbed entirely or it is emitted from the sample

X-ray absorption & “absorption edges”

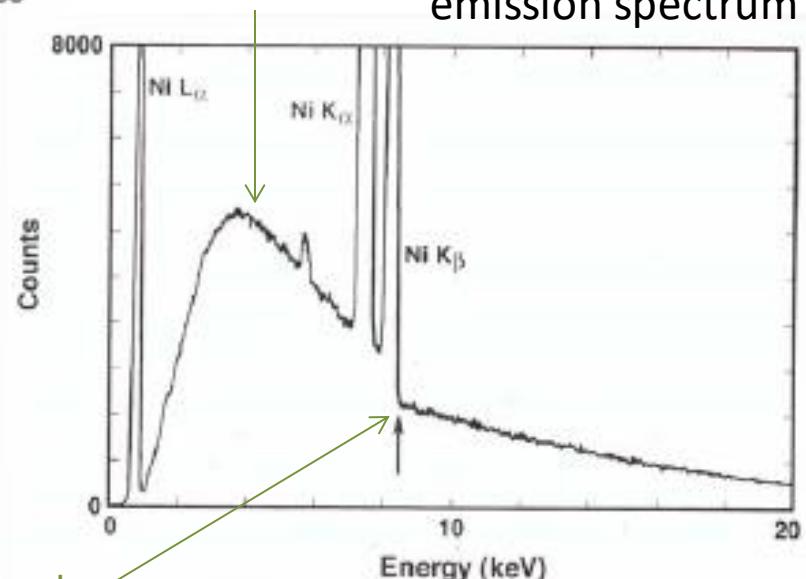
absorption spectrum



maximum absorption immediately above K X-ray absorption edge

background X-rays

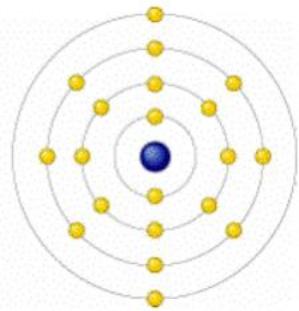
emission spectrum



No K x-rays produced
(by x-rays) when energy is
below K Ec

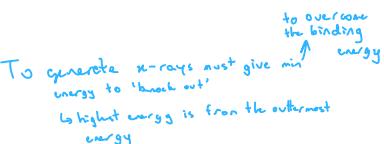
reflect how
it reflects
two graphs

abrupt decrease in background
intensity above the K edge due
to absorption by Ni

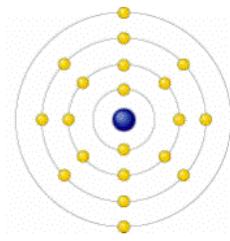


Absorption edge

- each electron in an atomic orbital ($1s$, $2s$, $2p$, $3s$ etc.) has a specific binding energy with the nucleus
- the closer the electron orbital is to the nucleus the higher its binding energy, $E_{K\text{-lines}} > E_{L\text{-lines}} > E_{M\text{-lines}}$
- the minimum energy required to completely remove an electron from orbital is known as the **critical edge** energy E_c (a.k.a. “ionisation potential”)
- electron beam energy must be greater than the critical edge, E_c to produce the X-ray



Platinum	Critical edge (keV)	X-ray Energy (keV)
K	78.39	66.83
L	11.56	9.442
M	2.133	2.051



X-ray self-absorption by a sample

Most x-rays must travel through the sample before leaving the surface

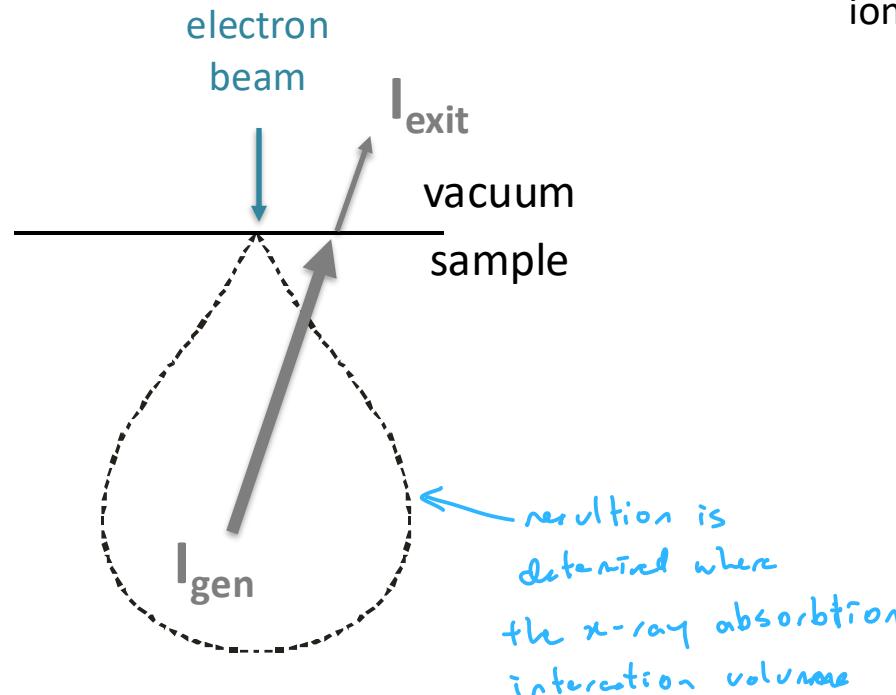
X-ray absorption follows Beer's law

$$I_{\text{exit}} = I_{\text{gen}} e^{-\mu S}$$

μ = mass attenuation coefficient

S = x-ray path length

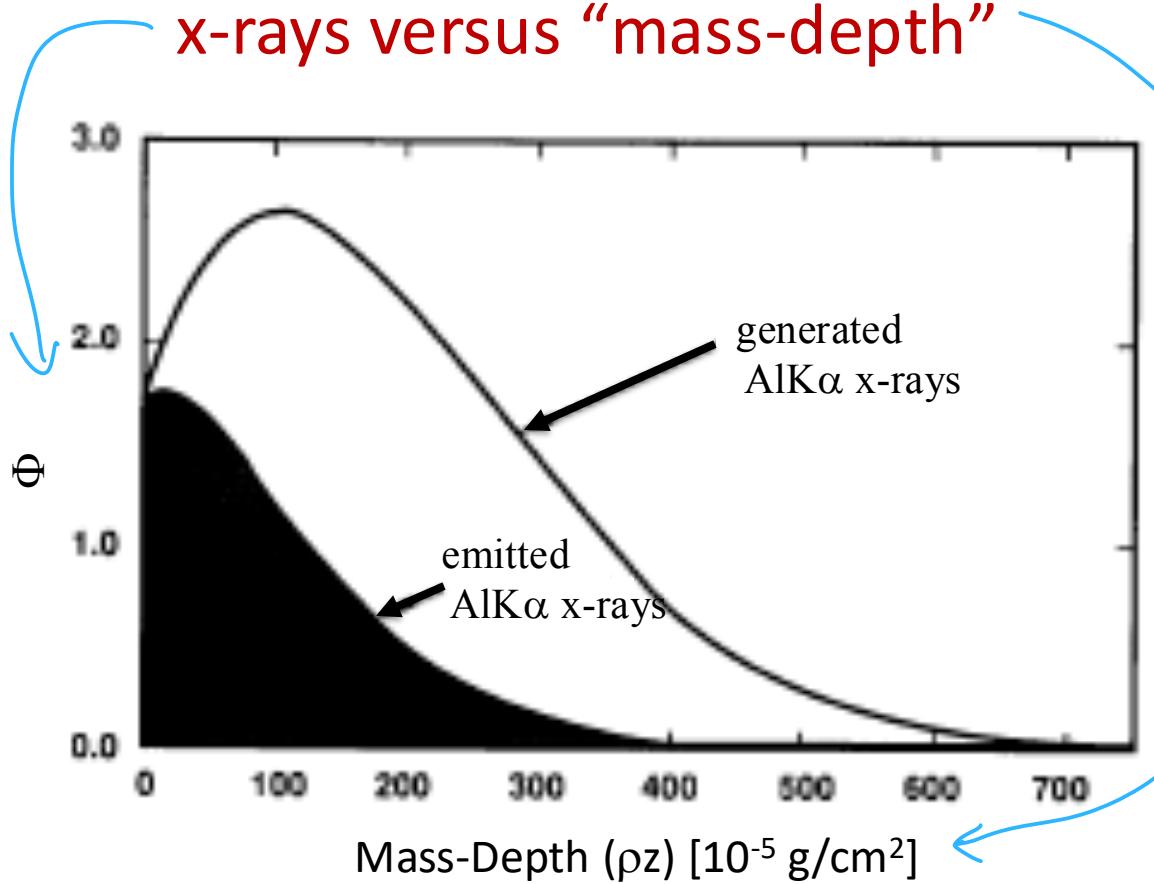
In the lab!



μ depends on energy of emitted X-ray and ionisation energies of atoms in sample

$\Phi(\rho z)$ curves

Distribution of generated and emitted x-rays versus “mass-depth”



$$\phi = f(\rho z)$$

ρ = mass density [g/m^3]
 z = depth [m]

electron beam

vacuum sample

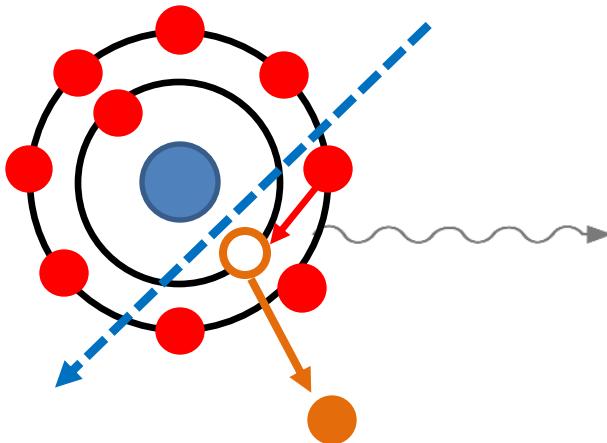
electron interaction volume

X-ray generation probability

Next slides for revision

1. ionisation probability
2. fluorescence yield (probability of x-ray emission upon de-excitation of ionized atom)
3. secondary fluorescence (due to x-ray self-absorption)

x-ray probability



Ionisation cross-section, Q [units: m²]

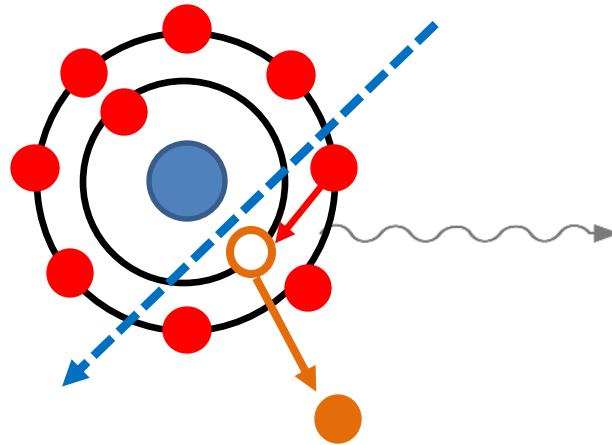
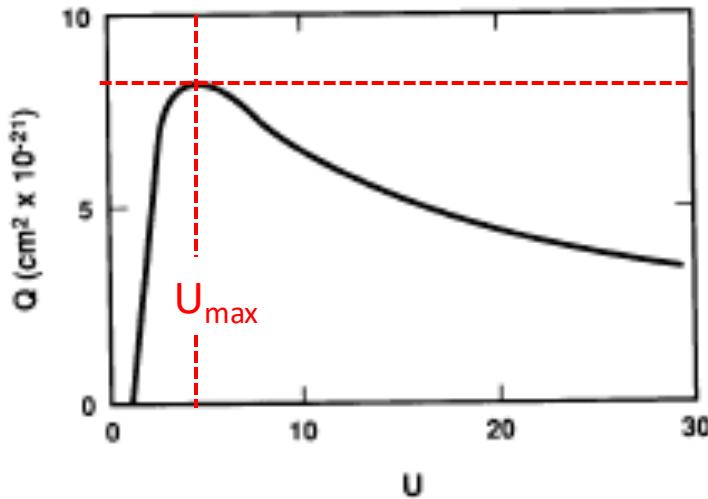
measure of ionisation probability

quantified

$$Q = \frac{C_1}{UE_C^2} \ln(C_2 U)$$

where U is the overvoltage ($U = E_o/E_c$)

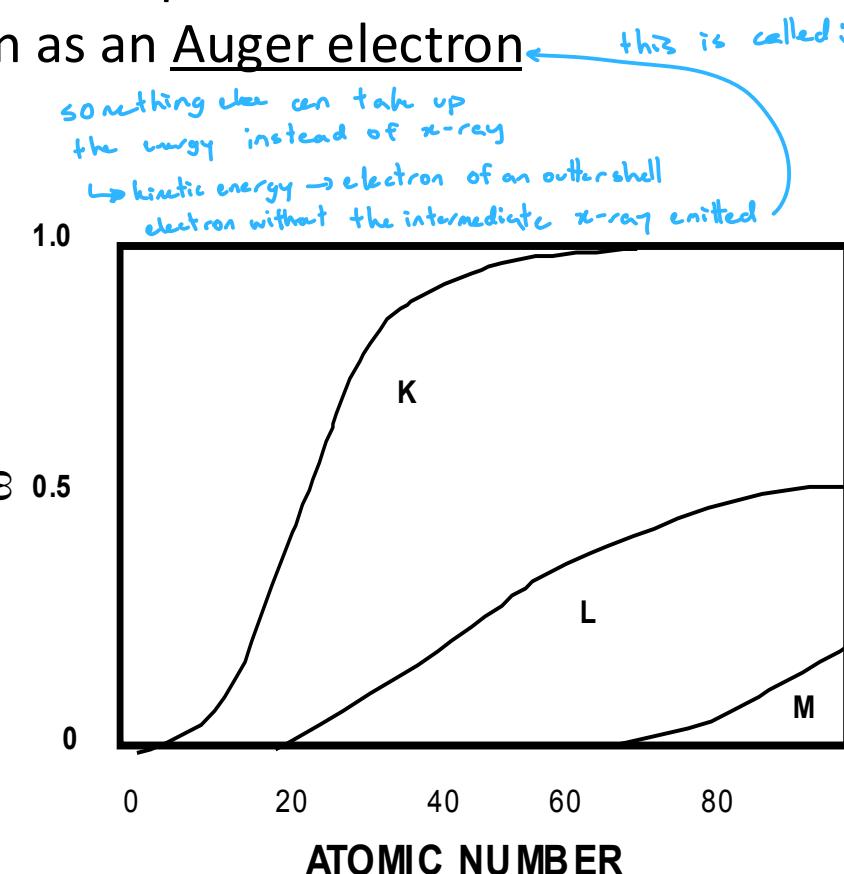
C_1 and C_2 are constants,
 E_c = critical edge,
 E_o = beam energy



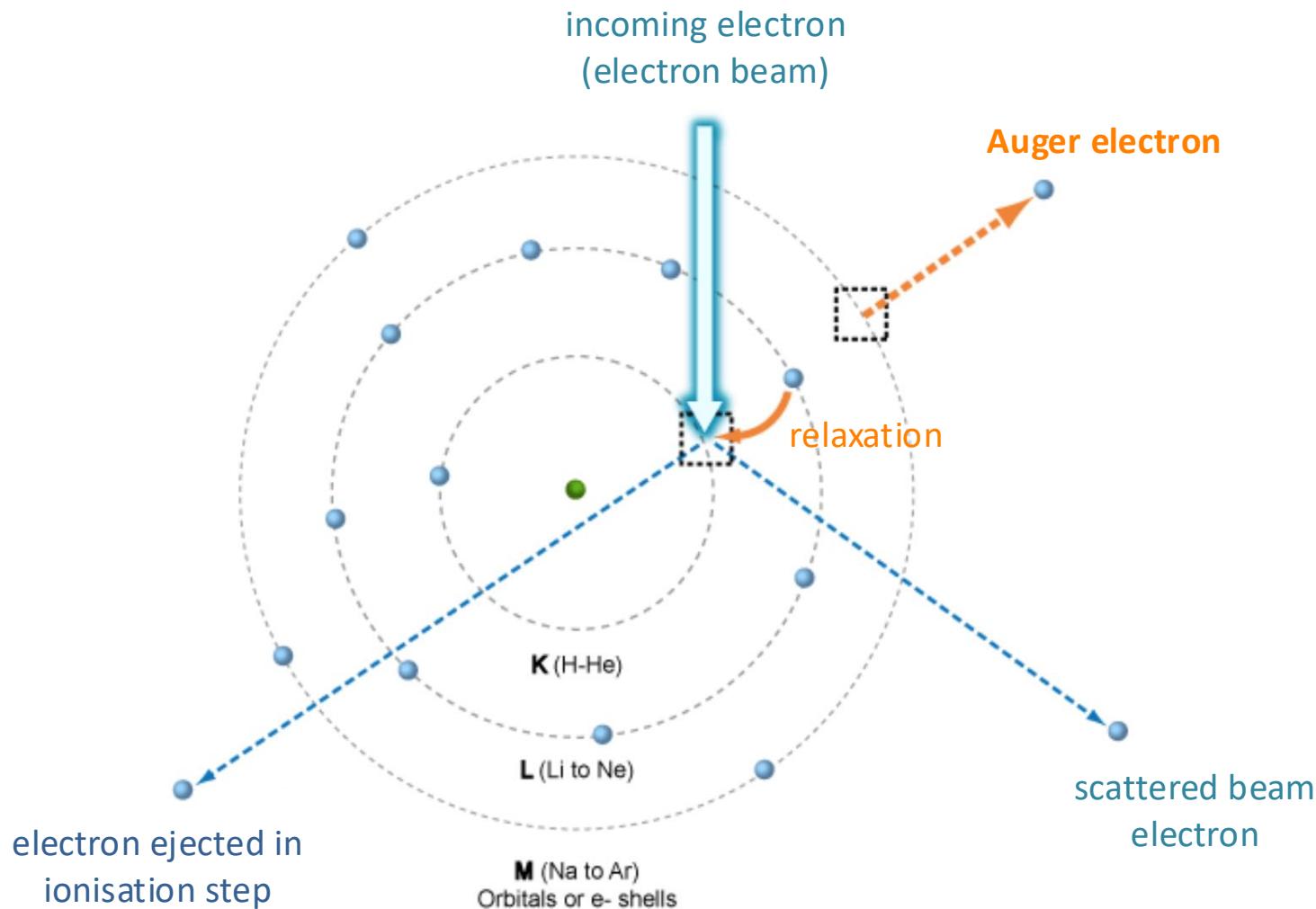
maximum number of ionisations
when $U \sim 3$ to 4 times E_c

Fluorescence Yield, ω [unitless]

- not all ionisations result in the production of an x-ray
- there is a certain probability that an excited atom will relax via a radiationless transition in which energy is dissipated via emission of an energetic outer shell electron, known as an Auger electron
this is called: something else can take up the energy instead of x-ray ↳ kinetic energy → electron of an outer shell electron without the intermediate x-ray emitted
- $\omega =$ the probability that an ionised atom will release a x-ray photon
- $(1-\omega) =$ probability that an ionised atom will release an Auger electron
- eg:
 - light elements (eg: C, N, O), ~ 1 in every 100 ionisation produces a K x-ray
 - transition metals (eg: Fe), ~ 1 in every 2 ionisations produces an x-ray

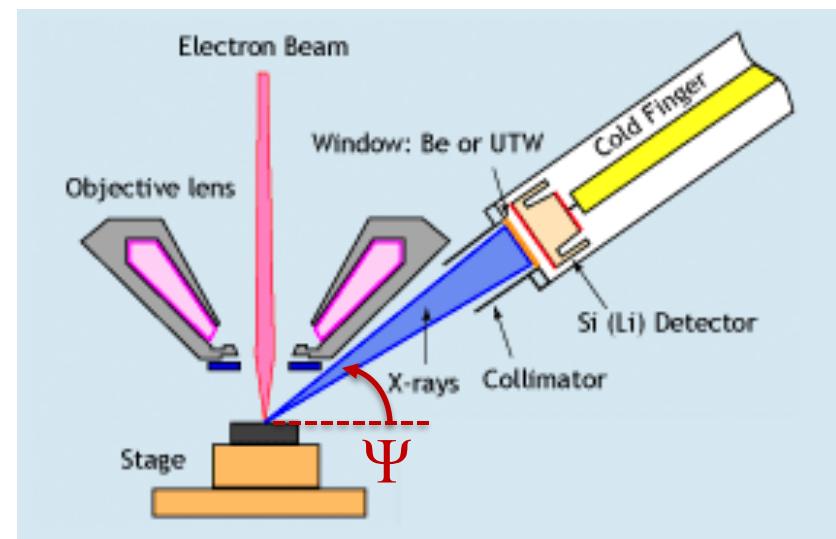
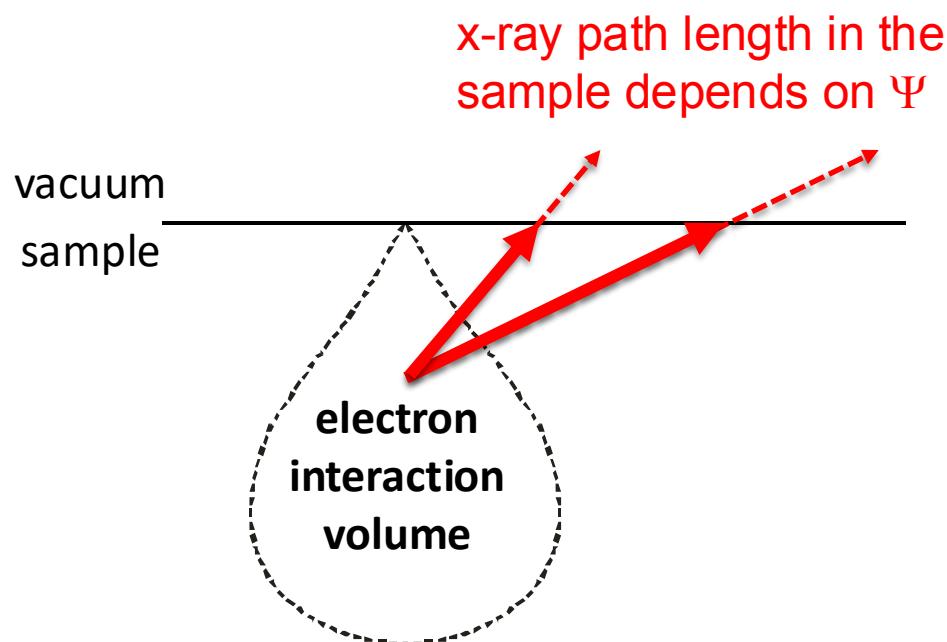


Auger electron emission



Secondary Fluorescence

- x-rays produced by other characteristic and background x-rays
- reduces the intensity of absorbed x-rays and increases the intensity of fluoresced x-rays
- affected by the x-ray escape depth, x-ray energy, sample composition and position of x-ray detector



- Ψ = “take-off angle”
- larger Ψ = less x-ray absorption
- Ψ limited by the the pole piece

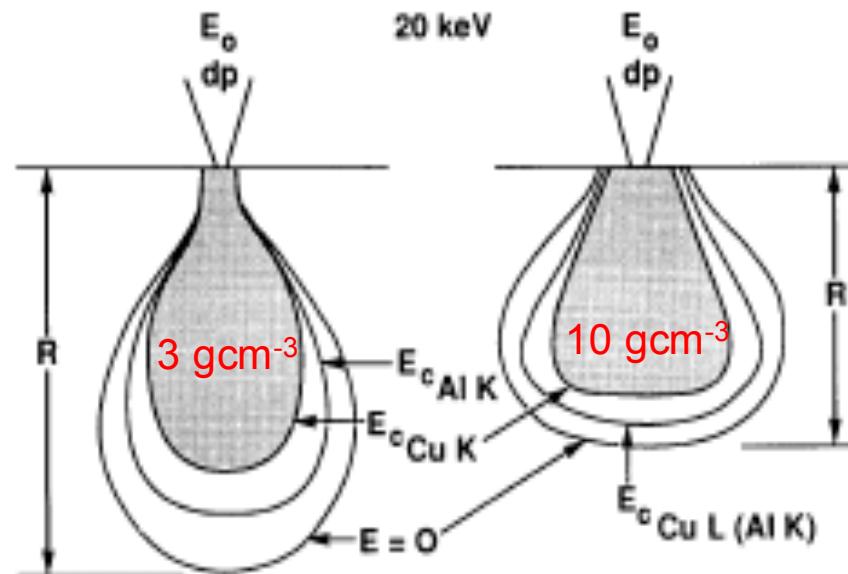
X-ray analysis spatial resolution

- determined by the x-ray range, not the beam diameter
- X-ray range (ie: maximum depth at which x-rays are generated) was determined by Anderson and Hasler:

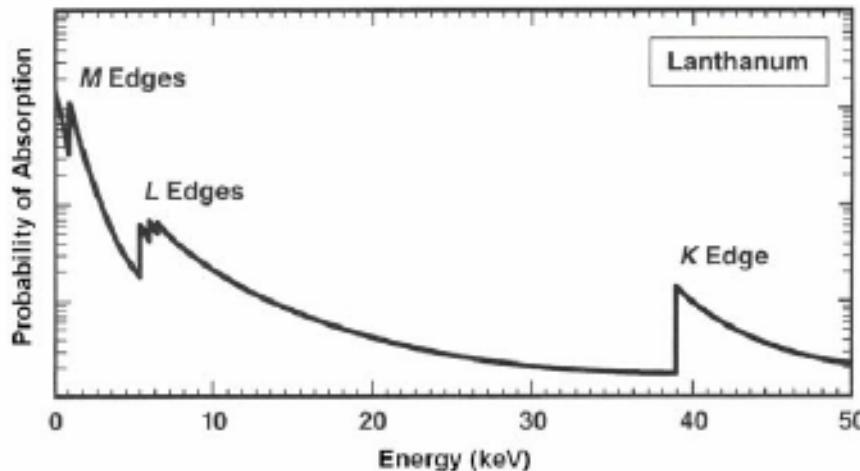
$$R_x = \frac{0.064(E_0^{1.68} - E_c^{1.68})}{r}$$

each x-ray line has its own
generation volume

R_x (μm) = x-ray range, E_0 (keV) = e beam energy, E_c (keV) = critical edge, ρ (gcm^{-3}) = density



X-ray absorption



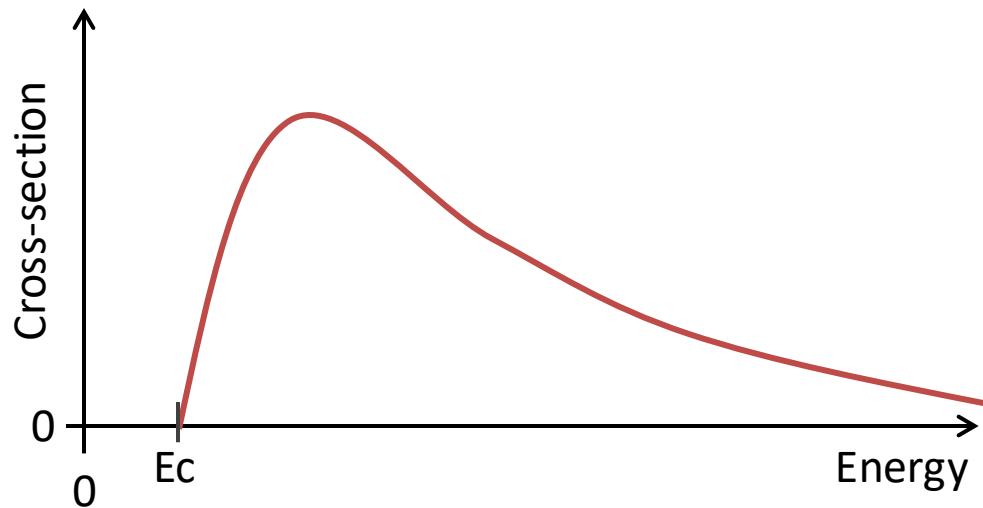
This x-ray absorption spectrum shows a number of so-called x-ray “absorption edges” for the element lanthanum. The edges are labelled K, L and M.

The K absorption edge is at energy E_a and the K x-ray has energy E_x .

Which statement is true?

- a) E_a is equal to the energy of Auger electrons emitted from lanthanum atoms.
- b) E_a is equal to E_x .
- c) E_a greater than E_x .
- d) E_a is smaller than E_x .

Cross-sections



The graph shows a cross-section that pertains to x-ray analysis in an electron microscope. Which statement is true?

- a) A cross-section can not equal to zero below the energy E_c . This is physically impossible and hence this plot must be incorrect.
- b) The units of a cross-section are the same as the units of probability (i.e., it is unitless).
- c) This is a cross-section for an electron relaxation transition that gives rise to x-ray emission.
- d) This is a cross-section for ionisation of an atom by an electron.
- e) The quantity on the horizontal axis is the energy of the emitted x-ray.

What's next?

Today

Tutorial 2: 12 PM

Thurs

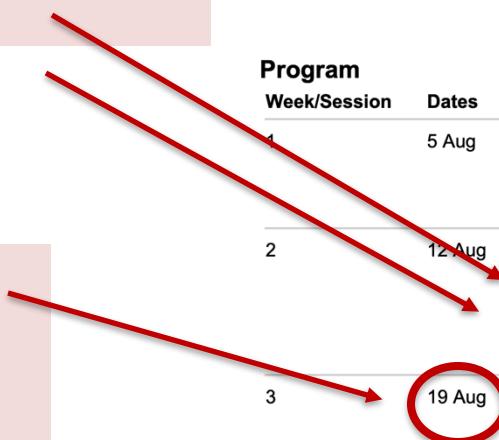
Prac 1: [see next slide]

Next week

Lecture 3: Tues

Tutorial 3: Tues

Lab 2: Thurs

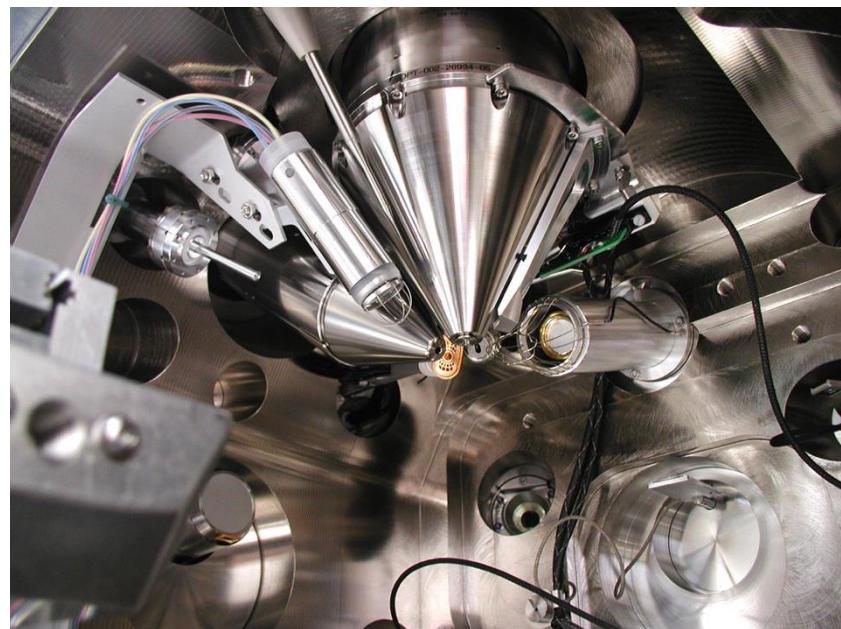
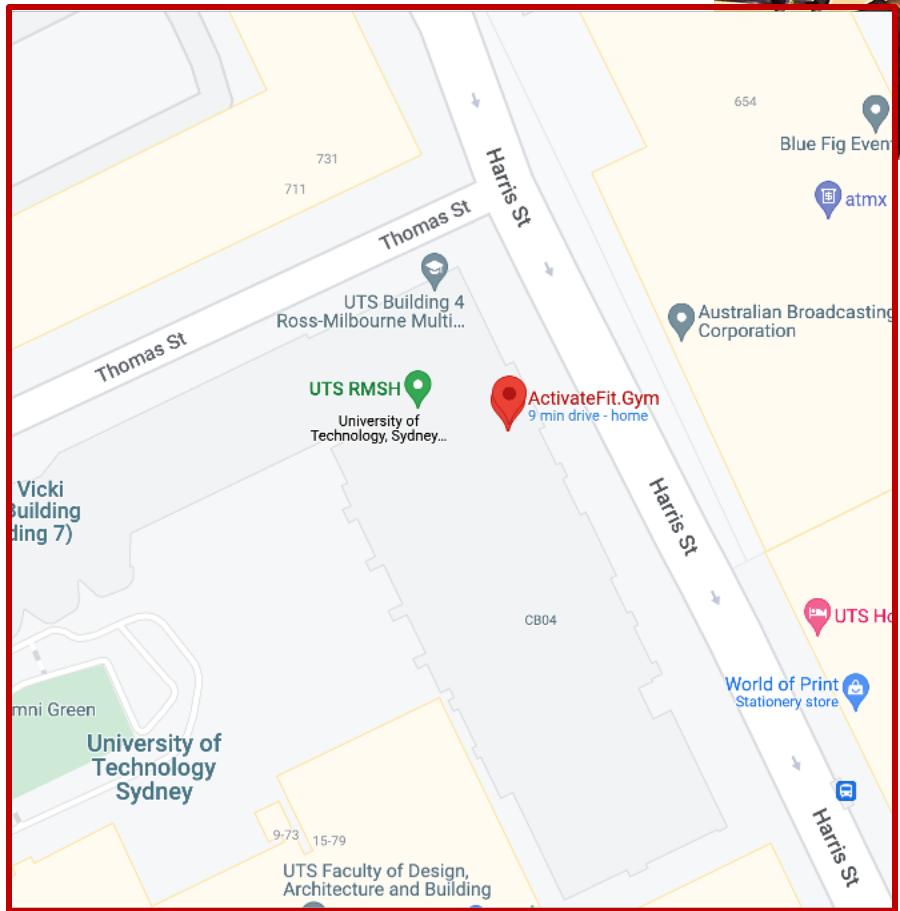
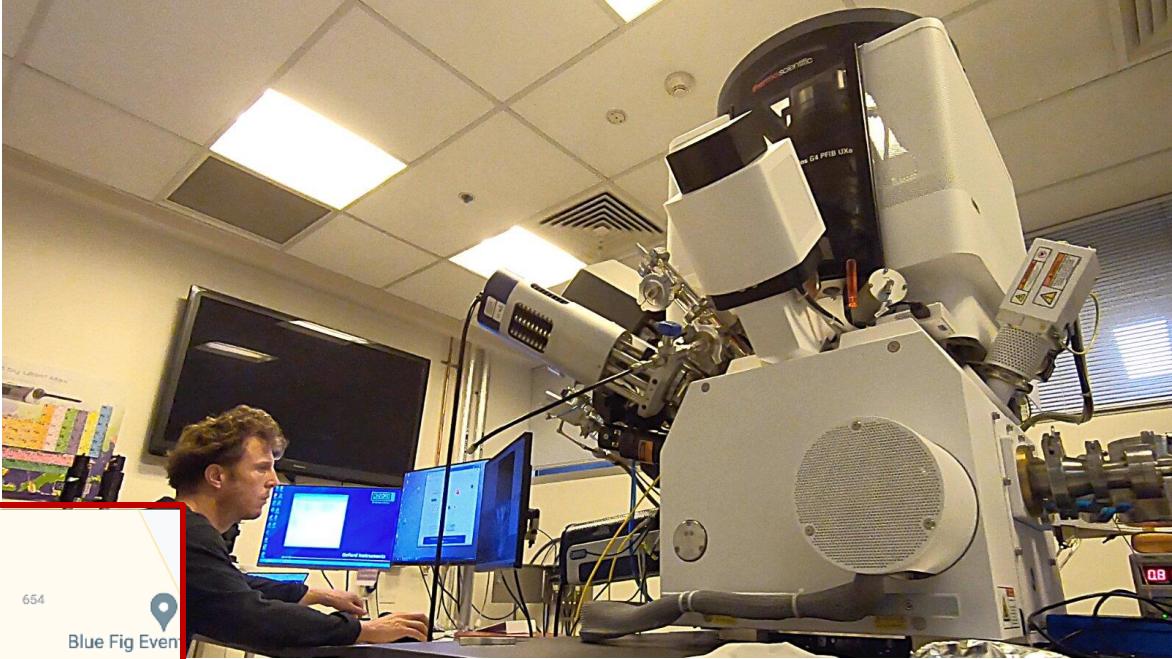


Program			
Week/Session	Dates	Description	
1	5 Aug	Lecture 1: Introduction	Tutorial 1: Nano-scale imaging basics
2	12 Aug	Lecture 2: Electron optics and electron-solid interactions	Tutorial 2: Electron-solid interactions Practical 1: Scanning electron microscopy
3	19 Aug	Lecture 3: Ion beams and electron/ion beam nanofabrication	Tutorial 3: Ion-solid interactions Practical 2: Electron/ion beam nanofabrication
4	26 Aug	CLASS TEST 1	
5	2 Sept	Lecture 4: Cathodoluminescence & x-ray analysis	Tutorial 4: Cathodoluminescence simulations Practical 3: Nanocharacterisation techniques
6	9 Sept	Lecture 5: Advanced nanocharacterisation	Practical 4: Nanocharacterisation techniques
7	16 Sept	Lecture 6: Ion-solid interactions and gas-assisted nanofabrication (advanced)	Portfolio 1 due this week (practicals) Portfolio 2 due this week (tutorials)
8	23 Sept	CLASS TEST 2	

Pracs

CB04.02.310

Corner of Harris & Thomas St
Near the UTS gym



Pracs: 1hour on Thursdays

- You will use 2 electron/ion beam labs
 - Lab safety rules: Max 8 students per lab
 - Class is split into 4 groups; find your group at [[Canvas → People → Groups](#)]
 - Groups 1 & 2 start at 1PM
 - Groups 3 & 4 start at 2 PM

Everyone Practical + Group set

Unassigned Students (0) Groups (4)

Search users

There are currently no students in this group. Add a student to get started.

Practical 1 8 students

- Mabel Acosta
- Henry Chen
- Jack Kelly
- Adam Lacey
- Yanzhong Su
- Elena Mbeya
- Shanti Woodend

Practical 2 8 students

- Nicola De Meio
- Emmanuel Haikalis
- Elvis Ly
- Hugh Radvan
- Shuai Lan
- Ryan Thomas

Practical 3 8 students

- Sajida Al-Rashid
- Cristian Corso
- Kevin Gao
- Minh Nguyen
- Yuto Yoshioka
- Albert Rust

Practical 4 8 students

- Binh Do
- Valeriya Karmazina
- Louis Mansfield
- Christian O'Donnell
- Pilili Zhang
- Samraat Mann
- Julia Pollock
- Tomas Zanni

1PM START

2 PM START

Everyone Practical + Group set

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